



Photonics Integrated Circuits for Free Space Communications

**Hongwei Zhao, Sergio Pinna, Bowen Song, Fengqiao Sang,
Simone Tommaso Šuran Brunelli, Larry Coldren,
Jonathan Klamkin**

hwzhao@ece.ucsb.edu

Outline

- ❖ **1. Background**
 - 1.1 Free space optical communications
 - 1.2 Photonic integrated circuits
- ❖ **2. Epi design**
 - 2.1 Epi structures
 - 2.2 Integration platforms
- ❖ **3. OQW-based PIC Transmitter**
 - 3.1 Fabrication process
 - 3.2 PIC characterization
 - 3.3 Free space link
- ❖ **4. QWI-based PIC Transmitter**
 - 4.1 Fabrication process
 - 4.2 PIC characterization
 - 4.3 High-power SOAs
- ❖ **5. Future work**

Outline

❖ 1. Background

1.1 Free space optical communications

1.2 Photonic integrated technologies

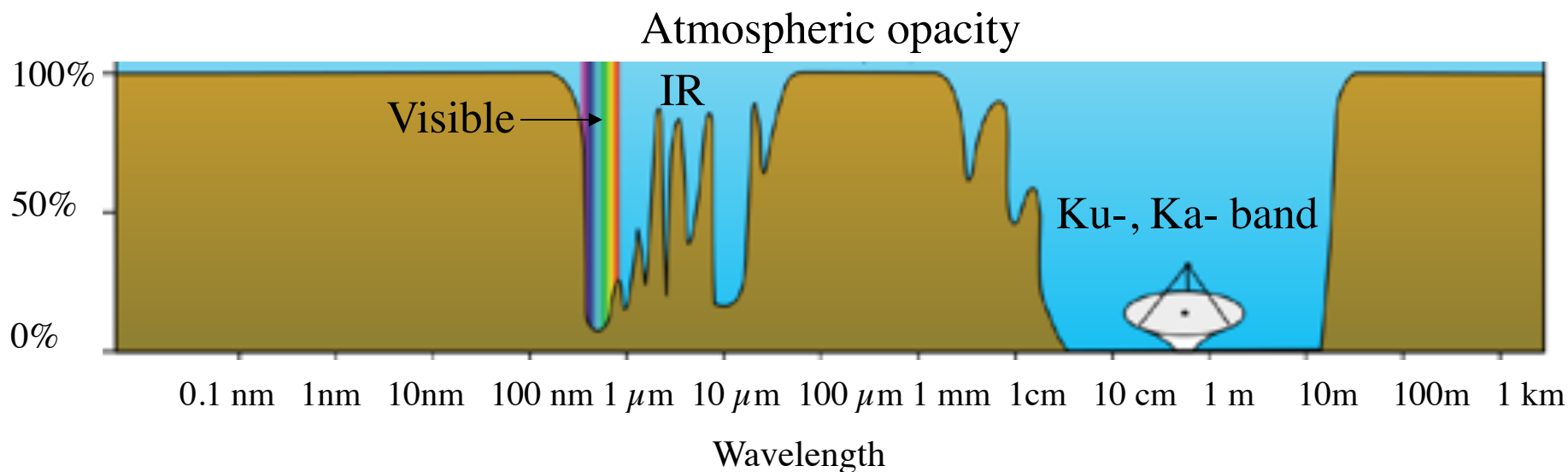
❖ 2. Epi design

❖ 3. OQW-based PIC transmitter

❖ 4. QWI-based PIC transmitter

❖ 5. Future work

1.1 Free space optical communication

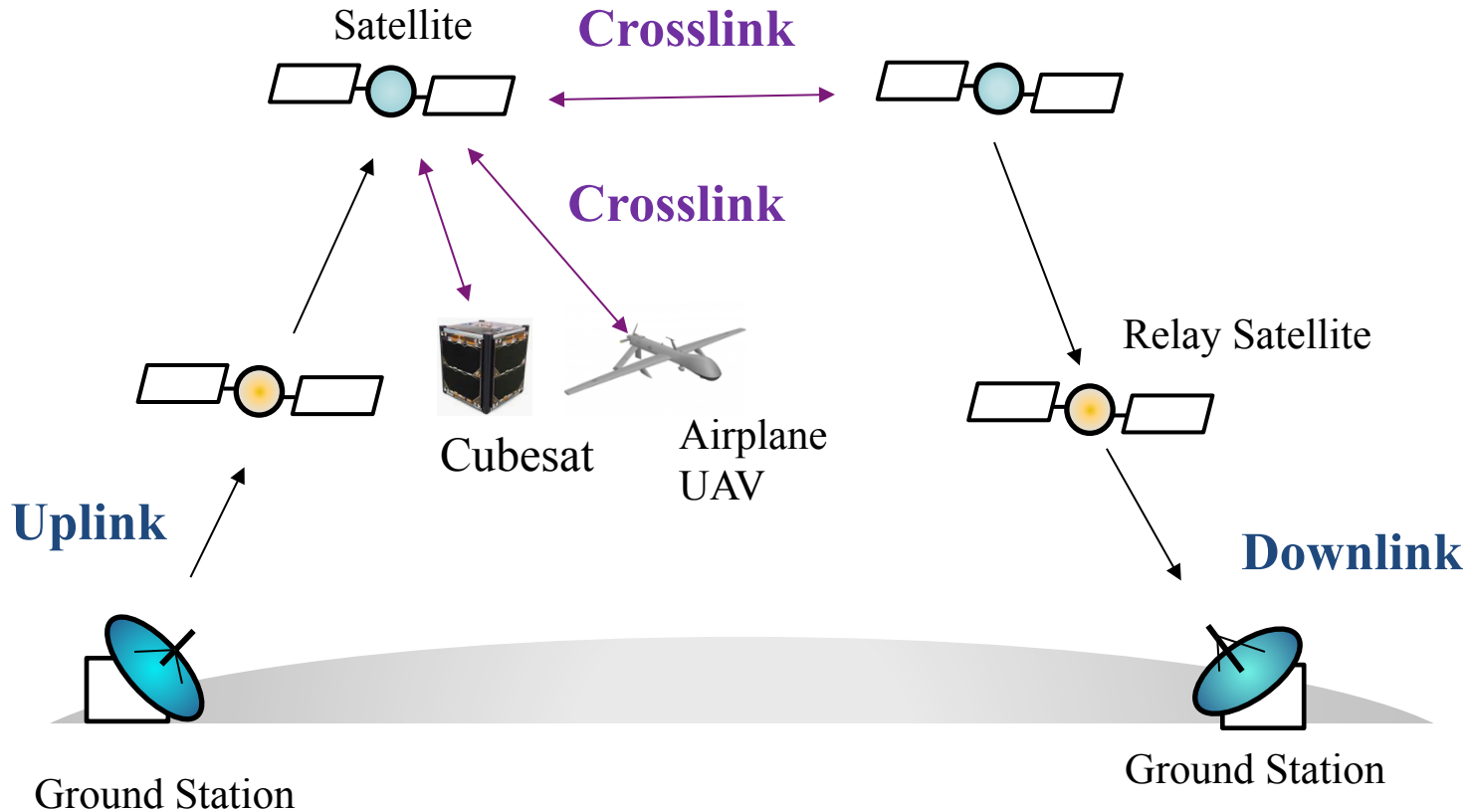


<https://gisgeography.com/atmospheric-window/>

Optical vs Radio frequencies

- Higher Data Rate
- Unlicensed Spectrum
- Easily expandable
- Less Power and Mass Requirement
- High Security
- Dependence on Weather Conditions

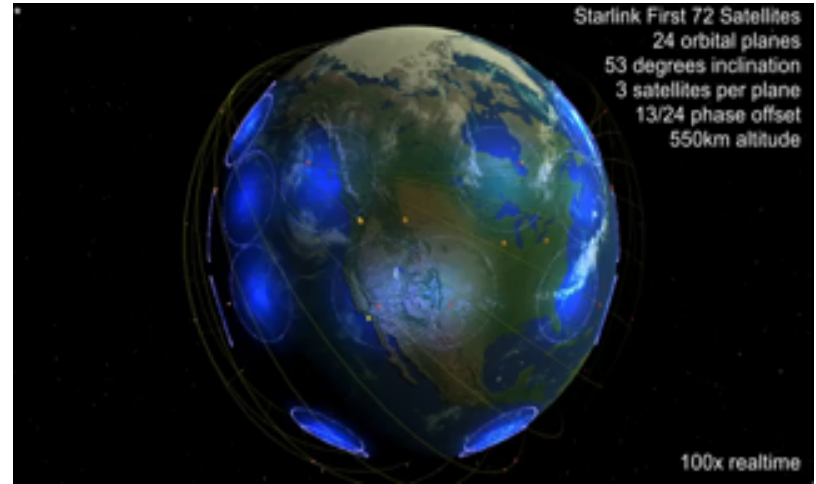
1.1 Free space optical communication



Space optical link architecture

1.1 Free space optical communication

Starlink Satellites by SpaceX

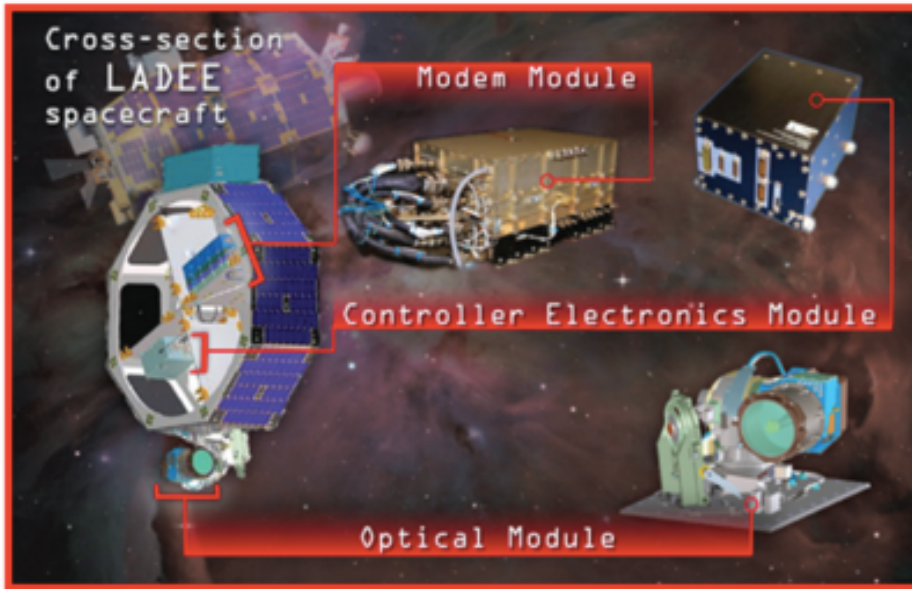


<https://www.spacex.com/>

- First 60 spacecraft of nearly 12,000 planned
- SpaceX wants to offer internet service after 6 launches
- Plans to complete Starlinks in 2027
- OneWeb, Telesat, Amazon have similar plans



1.1 Free space optical communication



<http://lcd.gsfc.nasa.gov>

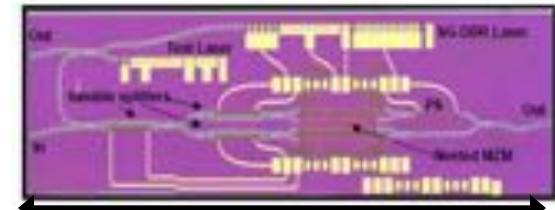
Lunar Laser Communication Demonstration

- Lunar-orbiting spacecraft \leftrightarrow Ground
- 20 Mbps uplink / 622 Mbps downlink



— 1 inch

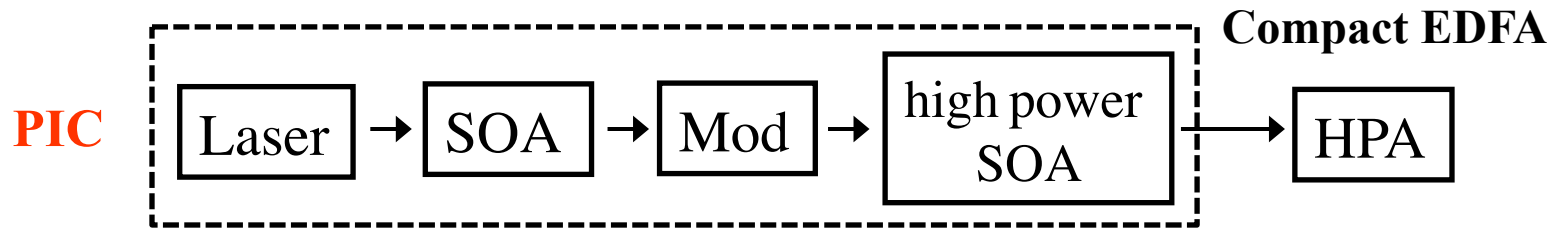
Photonic Integrated Circuits (PICs)



6 mm

**Significantly reduced
Cost, Size, Weight and Power
(CSWaP)**

1.1 Free space optical communication



Crosslinks
100 ~1000 m

LEO
links

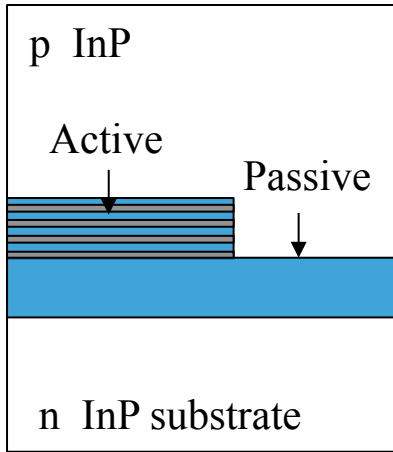
Deep space
links



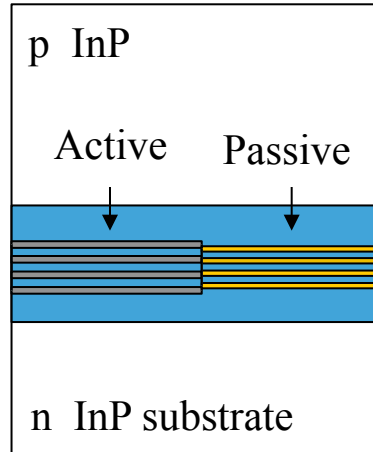
- Photonic integration → lower CSWaP
- Higher optical power → longer distance
- Power efficient modulation → increase peak power
- Couple with compact EDFA → very long distance

1.2 Photonic integrated technologies

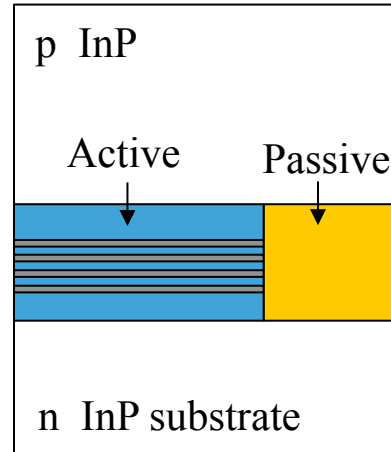
Integration Platforms for InP PICs



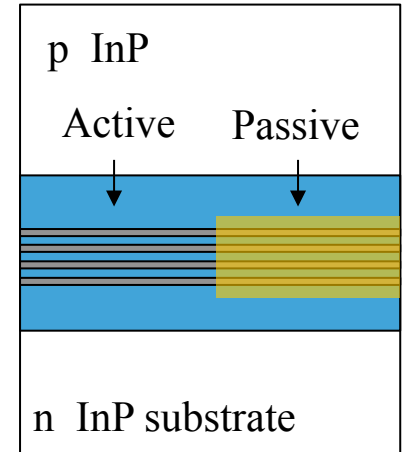
Offset Quantum Well (OQW)



Selective Area Growth (SAG)



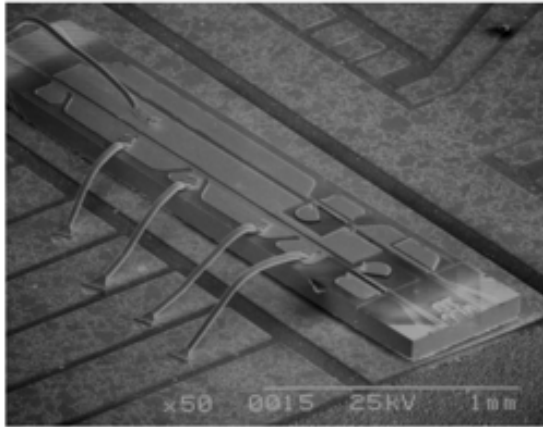
Butt Joint Growth (BJG)



Quantum Well Intermixing (QWI)

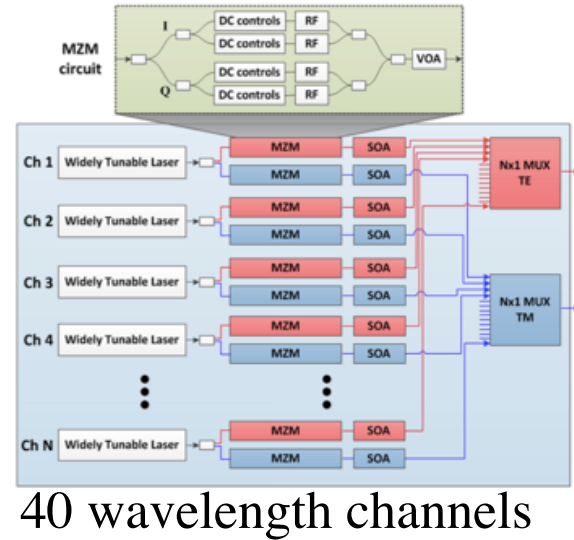
1.2 Photonic integrated technologies

SGDBR Laser/EA-Modulated Transmitter



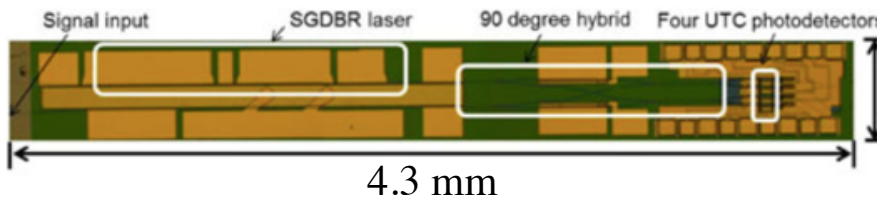
J. W. Raring et al., J. Lightwave Technol. 23, 80, 2005

Tunable Multi-Channel InP-Based Coherent Transmitter PICs

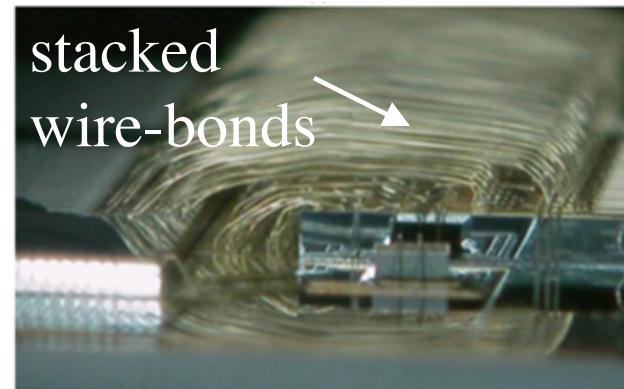


2 Tbps

InP-based optical-phase-locked loop (OPLL)



H. Park et al. Opt. Express, 20, 26, 2012



V. Lal et al., J. Lightwave Technology, 35, 7, 2017

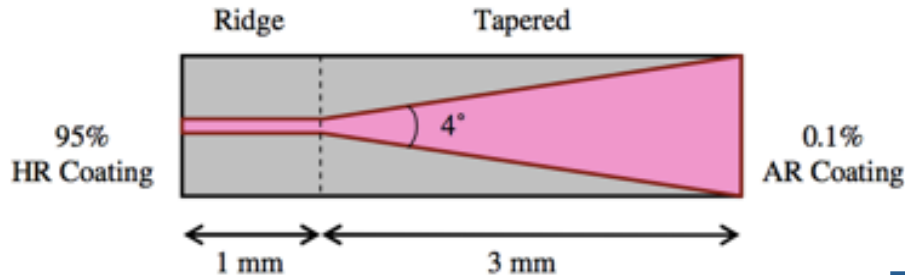
1.2 Photonic integrated technologies

Spectral efficiency



Power efficiency

Fared waveguide



H. Kwok et al. Proc. Opt. Fiber Commun., 2009

Highly asymmetric mode

Saturation power in SOAs:

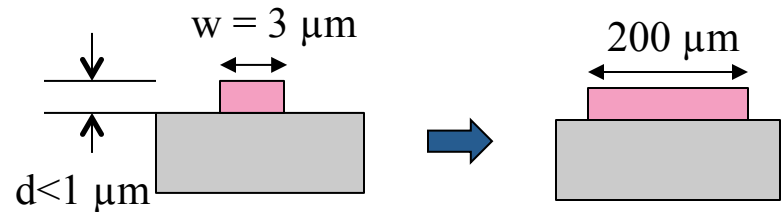
$$P_{o,sat} = \left(\frac{G_0 \ln 2}{G_0 - 2} \right) A \frac{h\nu}{a\tau}$$

$$A = \frac{wd}{\Gamma} \quad G_0 = e^{[(\Gamma g_0 - \alpha_i)L]}$$

A: mode cross-section area

Γ : confinement factor

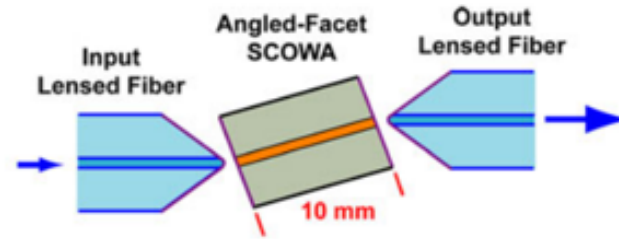
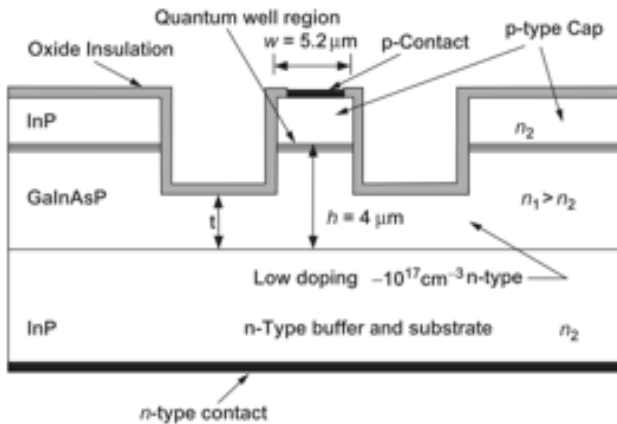
G_0 : unsaturated gain



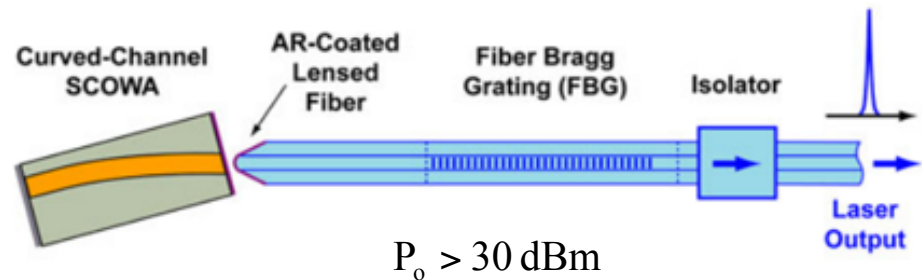
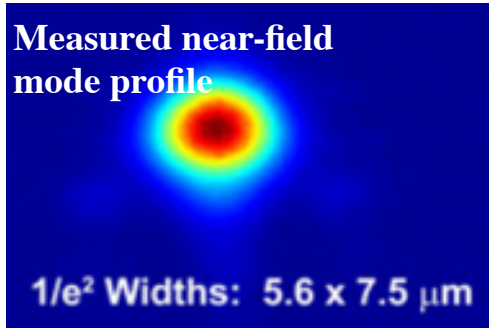
➤ **Beam quality (couple to fiber/space)**

1.2 Photonic integrated technologies

Slab-Coupled Optical Waveguide (SCOWL)



Traveling-wave SCOW amplifier



$P_o > 30$ dBm

Single-frequency SCOW external-cavity laser

P. Juodawlkis et al., JSTQE, 17(6), 2011

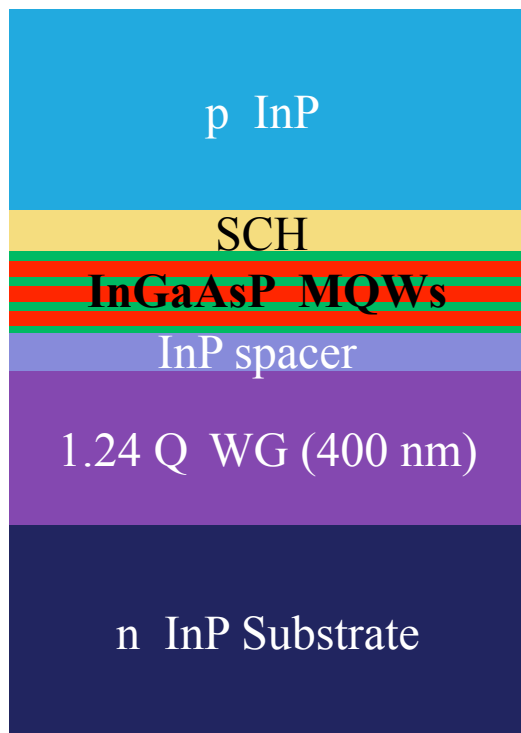
➤ Integration of laser/modulator and SOA

Outline

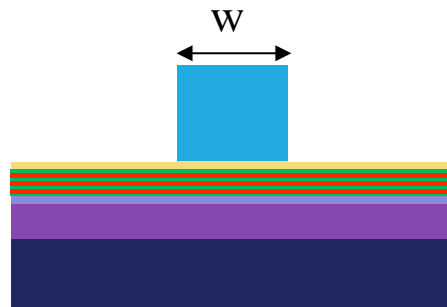
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2.1 Epi structures

Epi structure S1

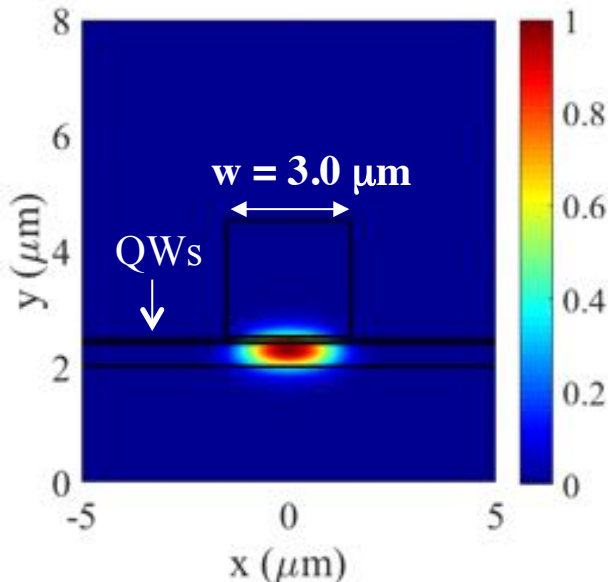


Surface ridge WG



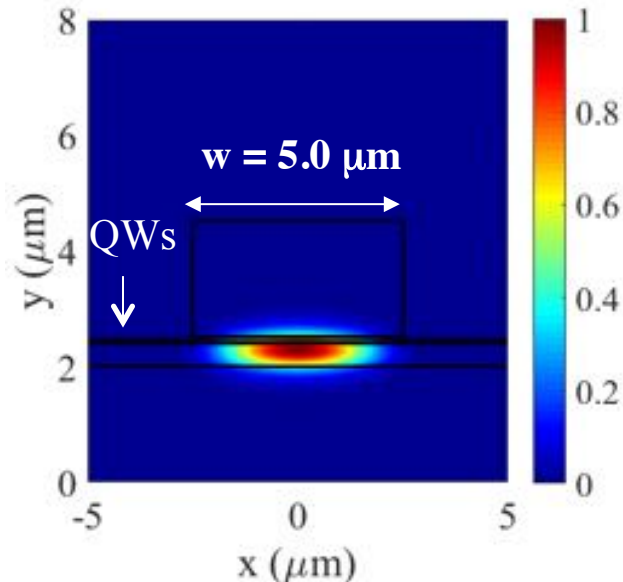
$\lambda = 1550 \text{ nm}$

Laser/Mod



$A = 2.23 \mu\text{m}^2 \quad \Gamma = 4.16\%$

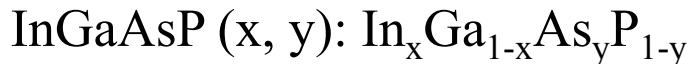
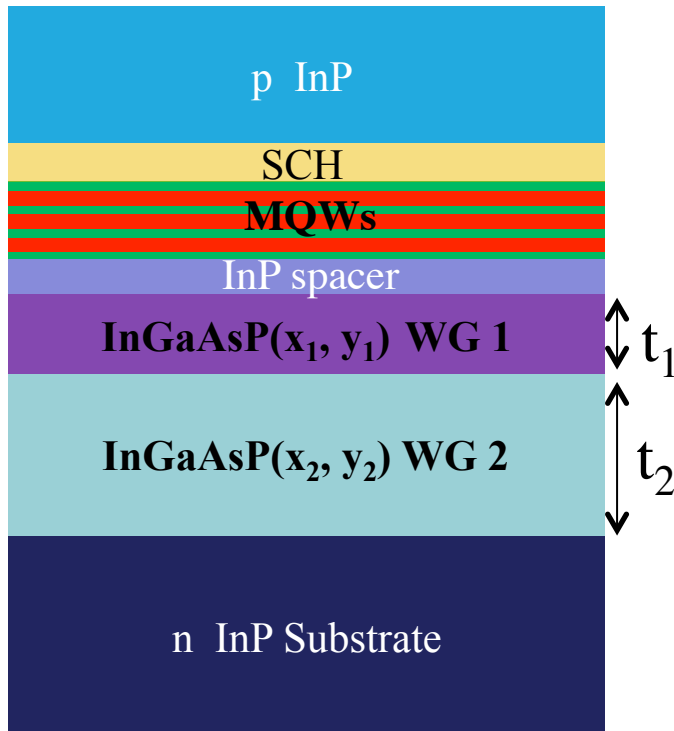
SOA



$A = 3.24 \mu\text{m}^2 \quad \Gamma = 4.23\%$

2.1 Epi structures

Epi structure S2



$$P_{o,sat} = \left(\frac{G_0 \ln 2}{G_0 - 2} \right) A \frac{h\nu}{a\tau}$$

$$\uparrow A = \frac{wd}{\Gamma} \downarrow$$

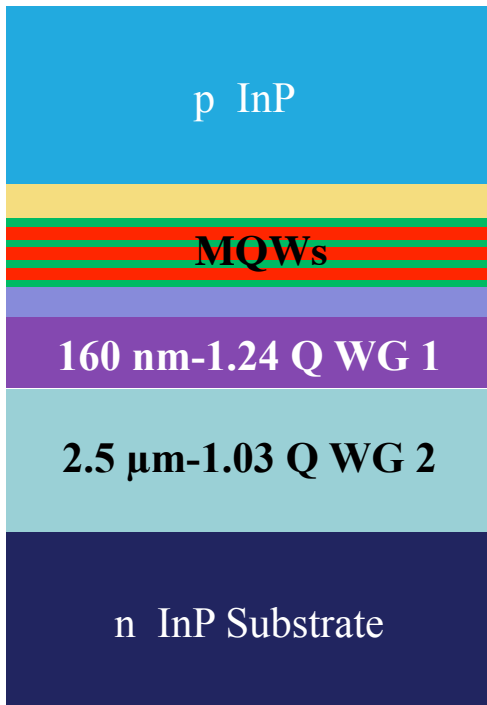
x_1, y_1, t_1
 x_2, y_2, t_2
 WG structures



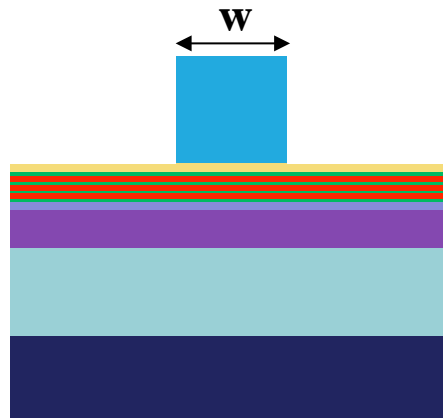
1. Low Γ and large modal area in SOA;
2. Relative high Γ in laser/modulator.

2.1 Epi structures

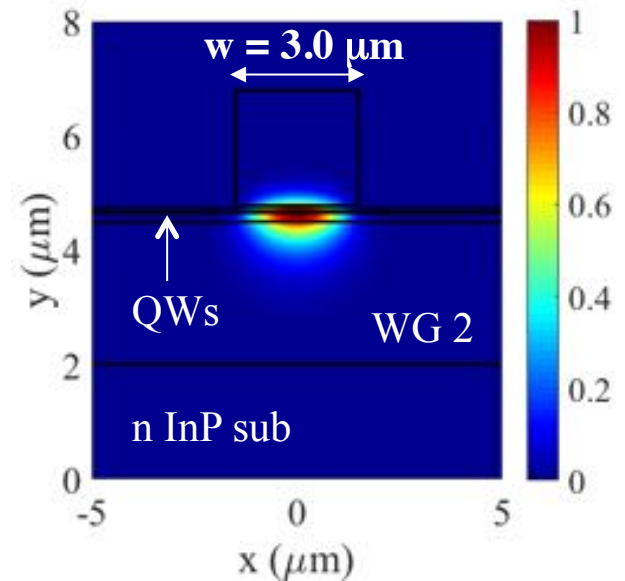
Epi structure S2



Surface ridge WG



Laser/Mod



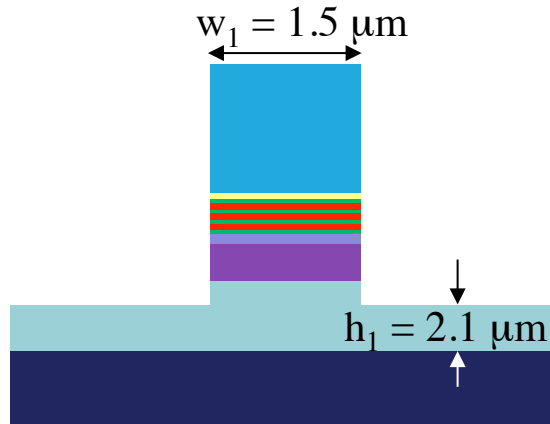
$A = 3.37 \mu\text{m}^2 \quad \Gamma = 3.73\%$

Epi structure S1: $A = 2.23 \mu\text{m}^2 \quad \Gamma = 4.16\%$

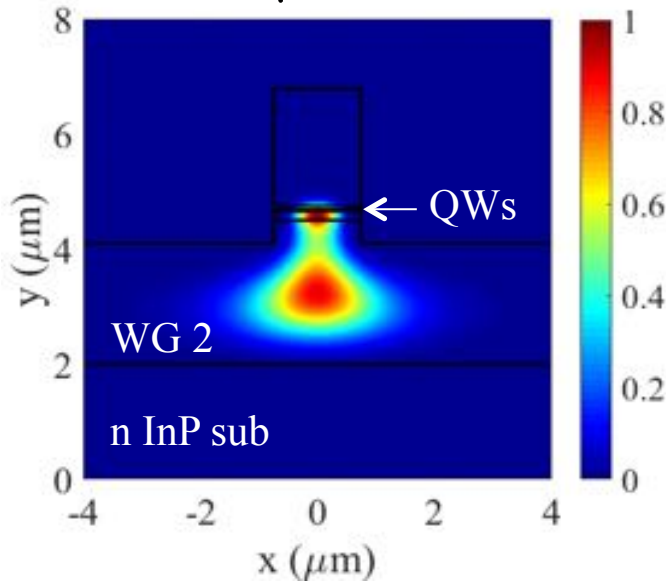
2.1 Epi structures

High-power SOA

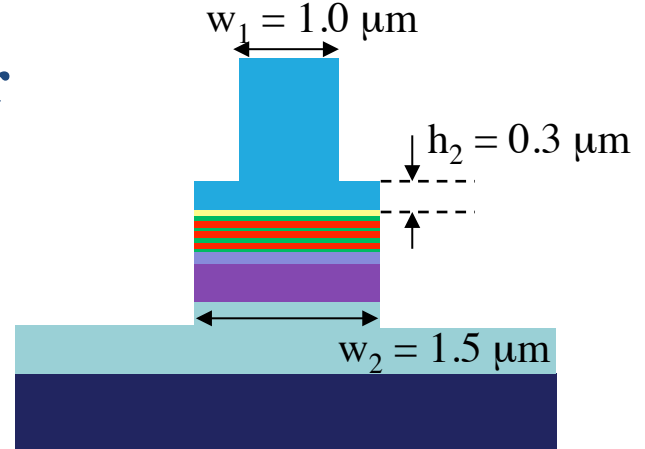
Single ridge WG



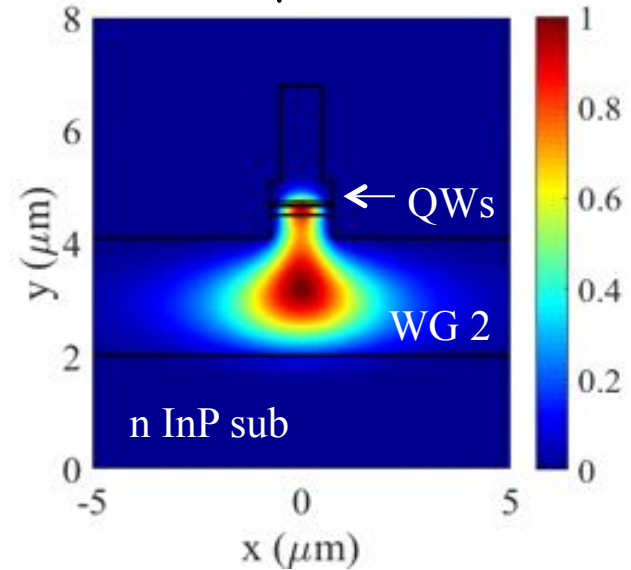
$A = 10.97 \mu\text{m}^2 \quad \Gamma = 0.41\%$



Double ridge WG

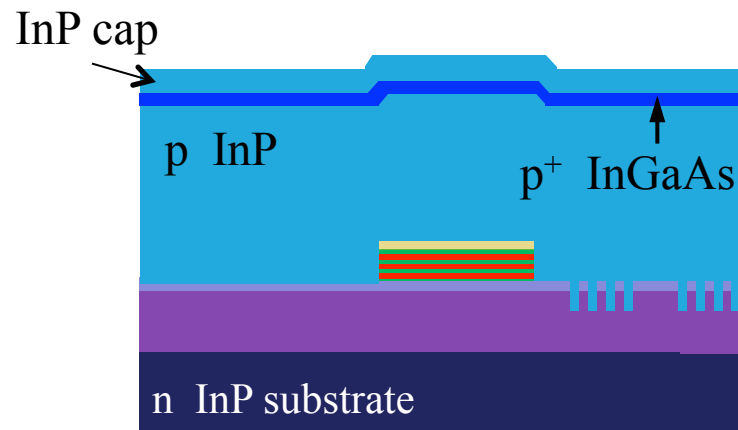


$A = 11.37 \mu\text{m}^2 \quad \Gamma = 0.35\%$

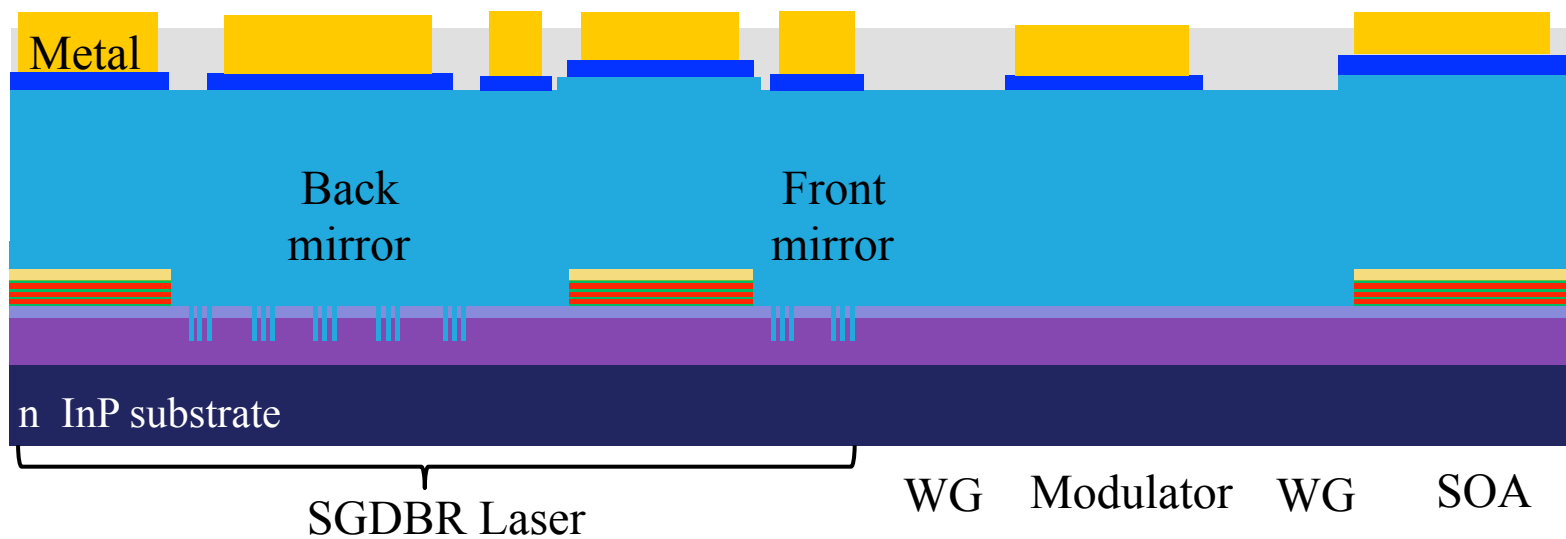


2.2 Integration platforms

Gen 1 Tx based on OQW

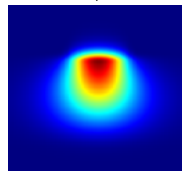
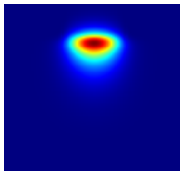
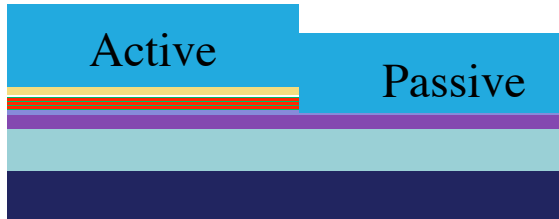


Epi structure S1 after regrowth

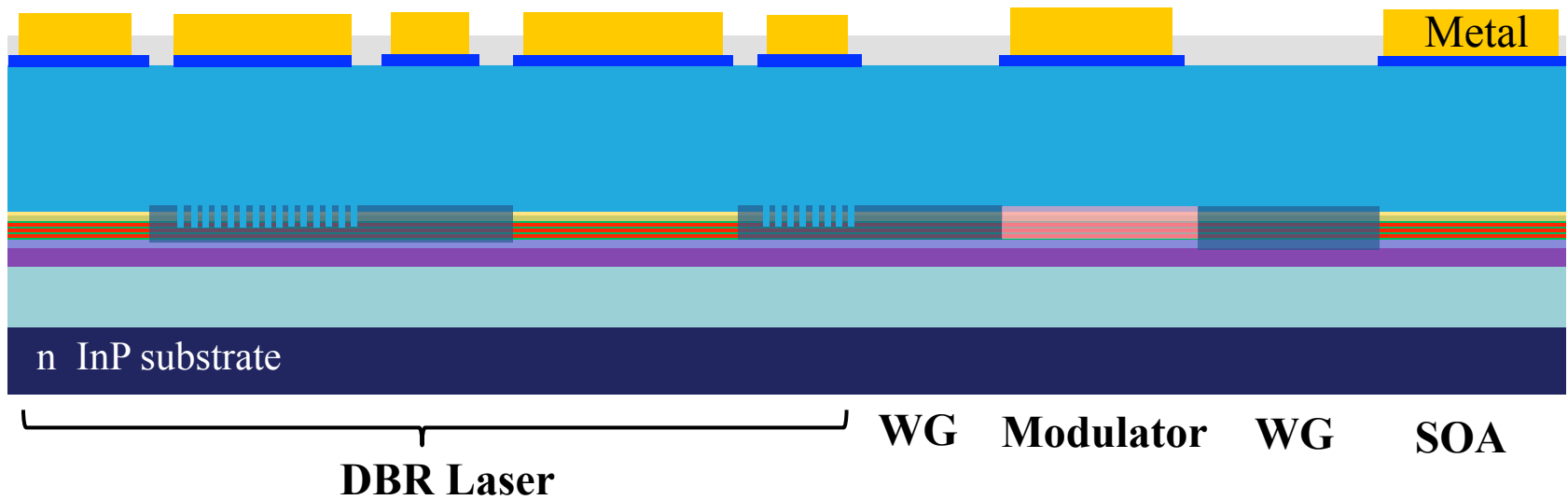


2.2 Integration platforms

Epi structure S2



Gen 2 Tx based on QWI

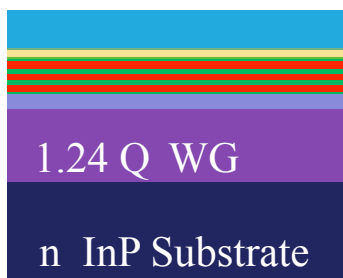


Outline

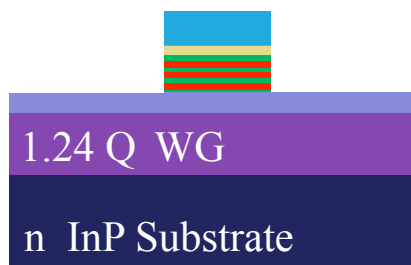
- ❖ 1. Background
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 - 3.2 PIC characterization
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3.1 Fabrication process

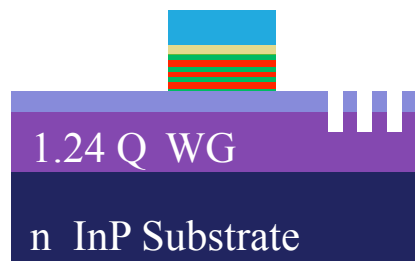
Epi structure S1



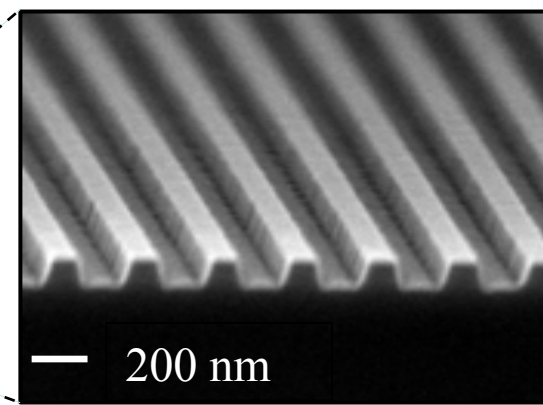
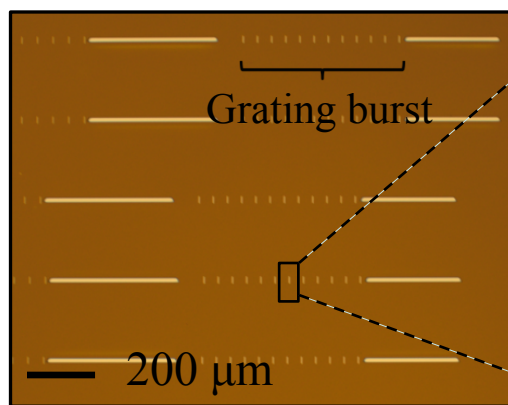
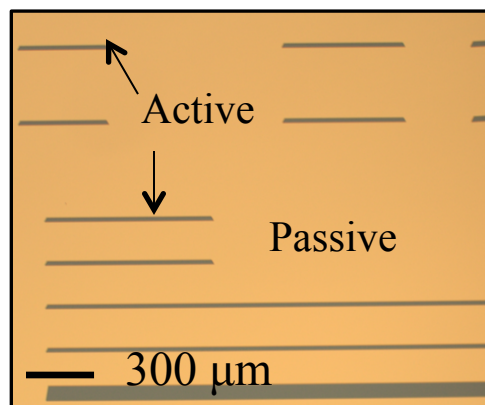
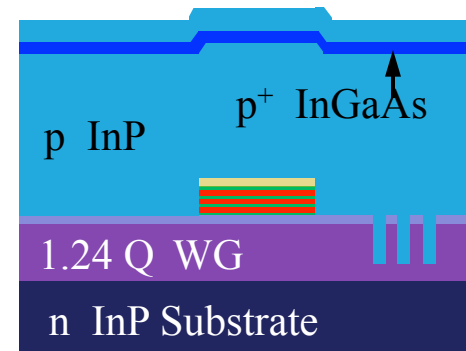
1. Active/Passive



2. Grating Etch

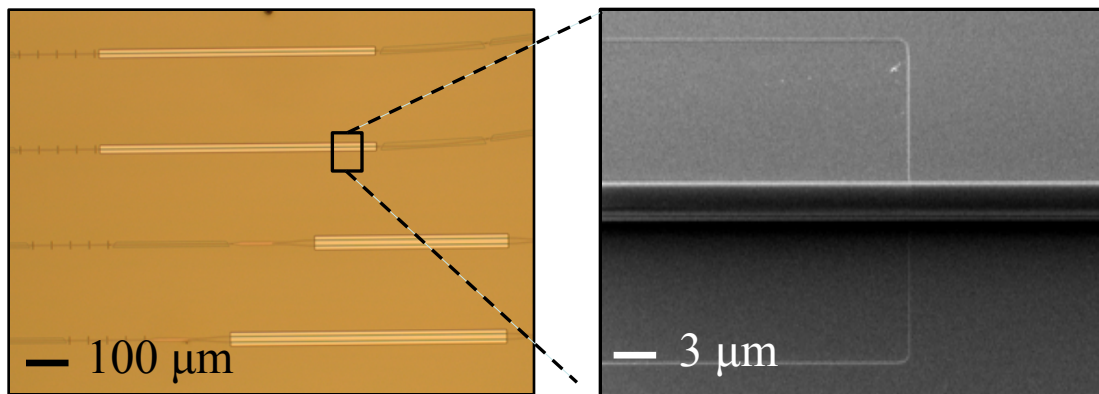
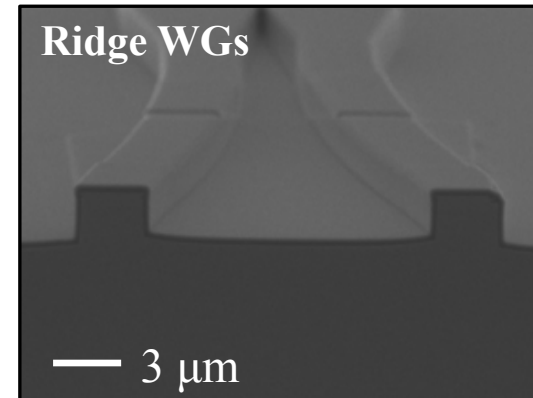
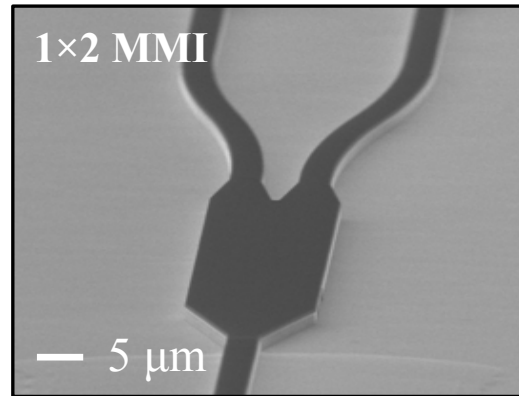
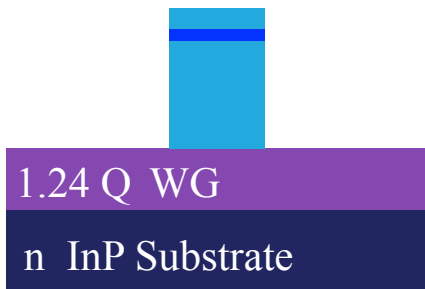


3. Regrowth

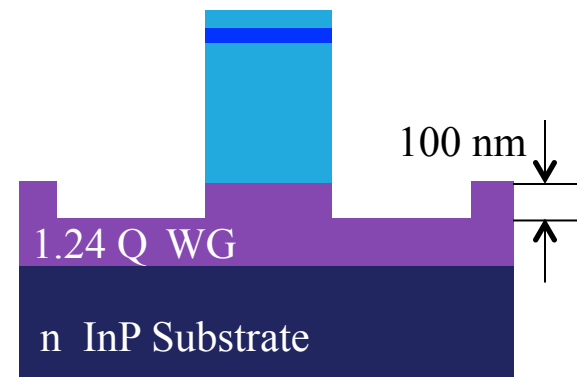


3.1 Fabrication process

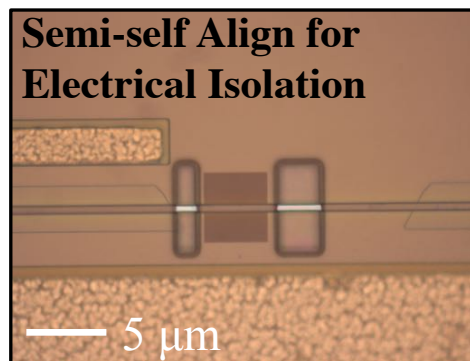
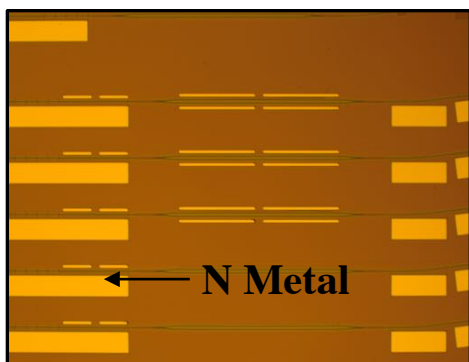
4. Ridge etch



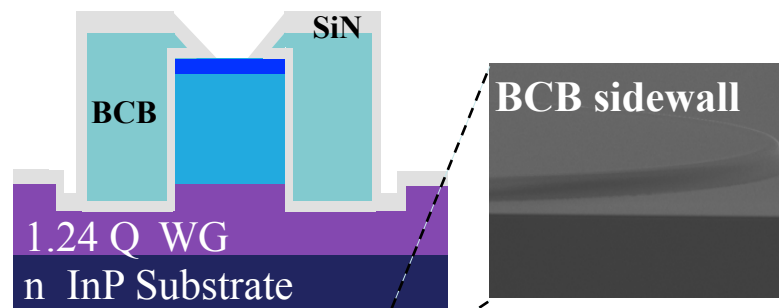
5. Passivation Etch



3.1 Fabrication process

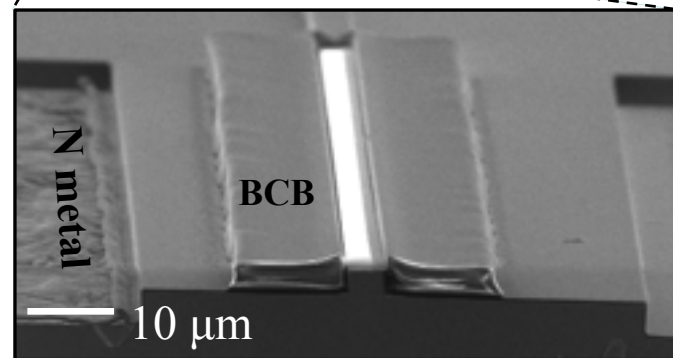
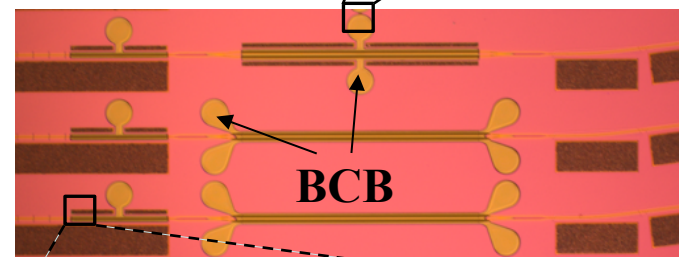
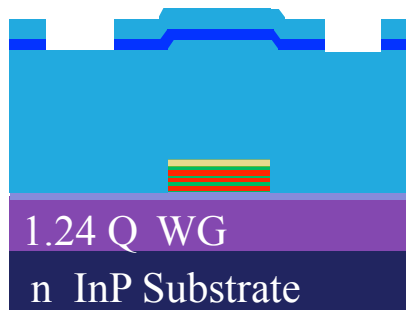
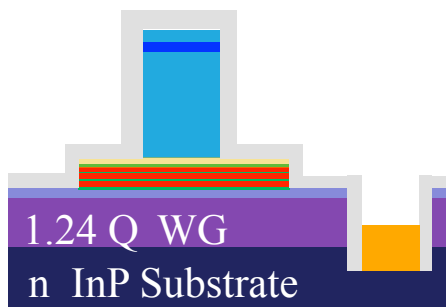


9. BCB Pattern 10. BCB via



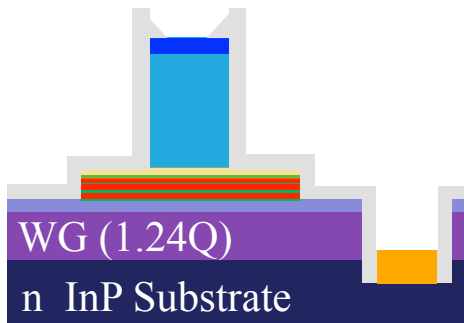
6. N hole etch
7. N metal liftoff

8. Isolation

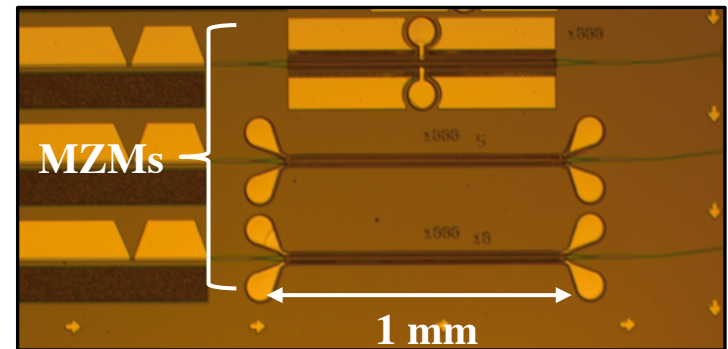
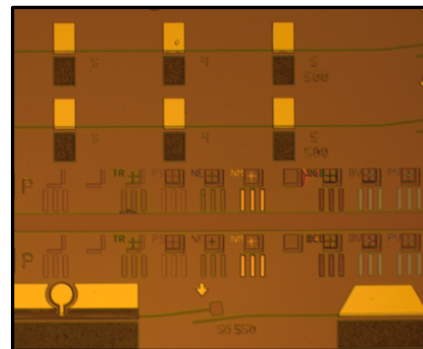
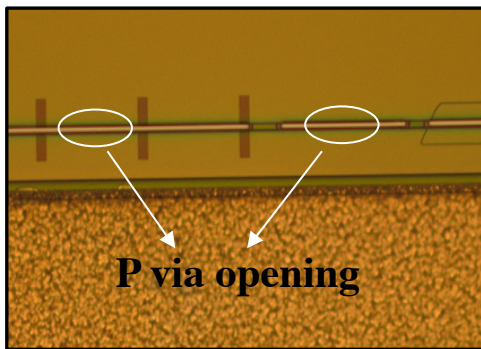
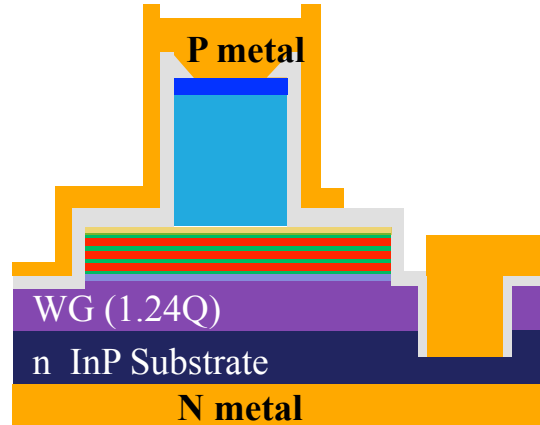


3.1 Fabrication process

11. P Via

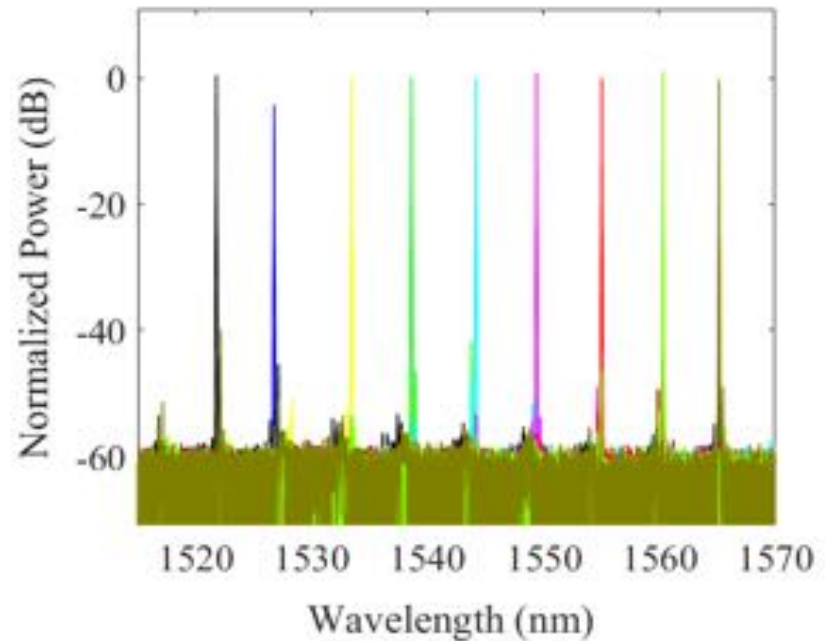
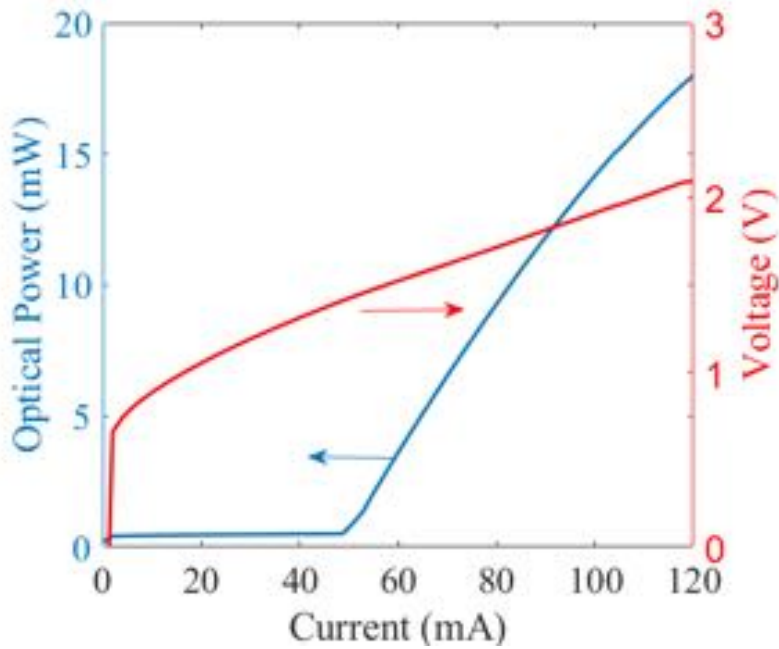
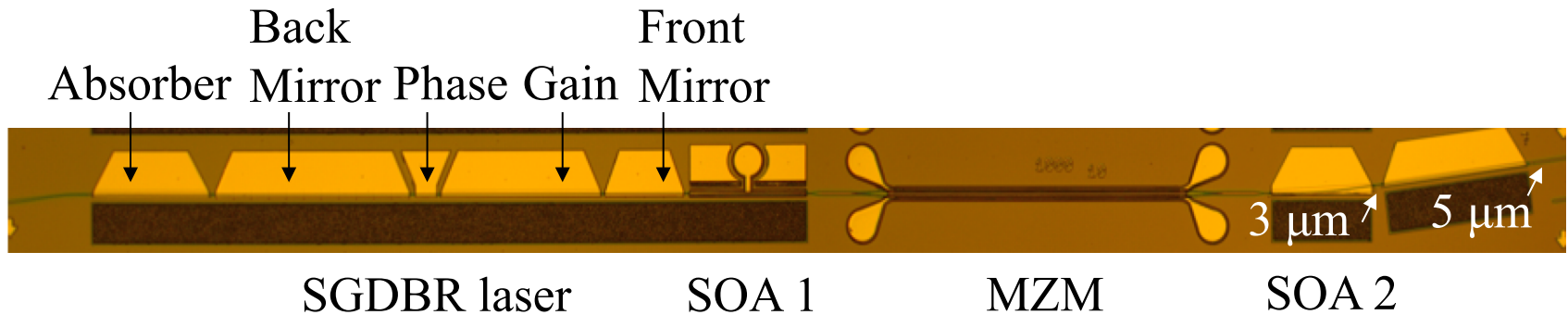


12. P Metal
13. Backside N contact



Vernier and test structures

3.2 PIC characterization

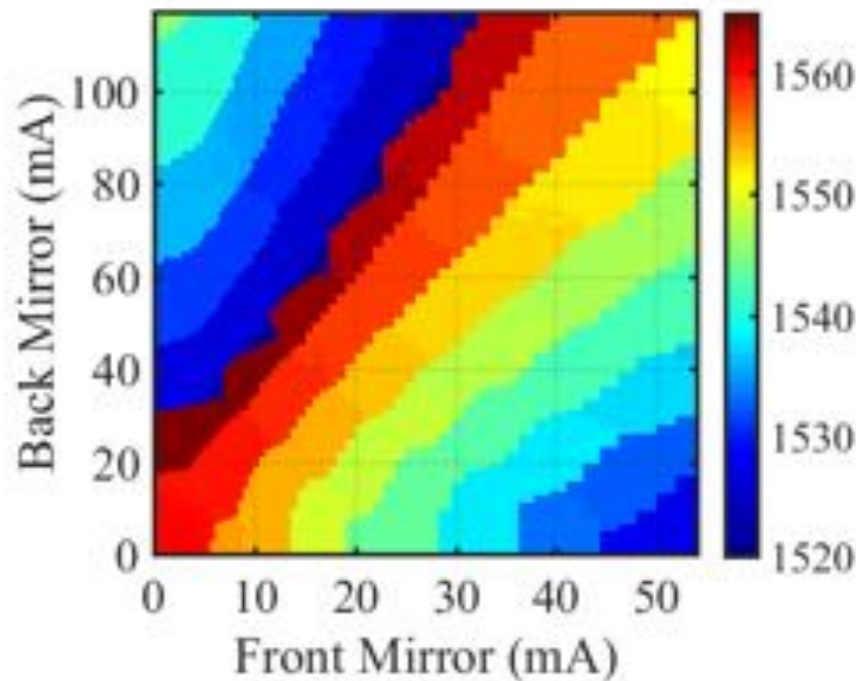


CW Light-Current-Voltage (LIV) characteristic

1521 nm ~ 1565 nm

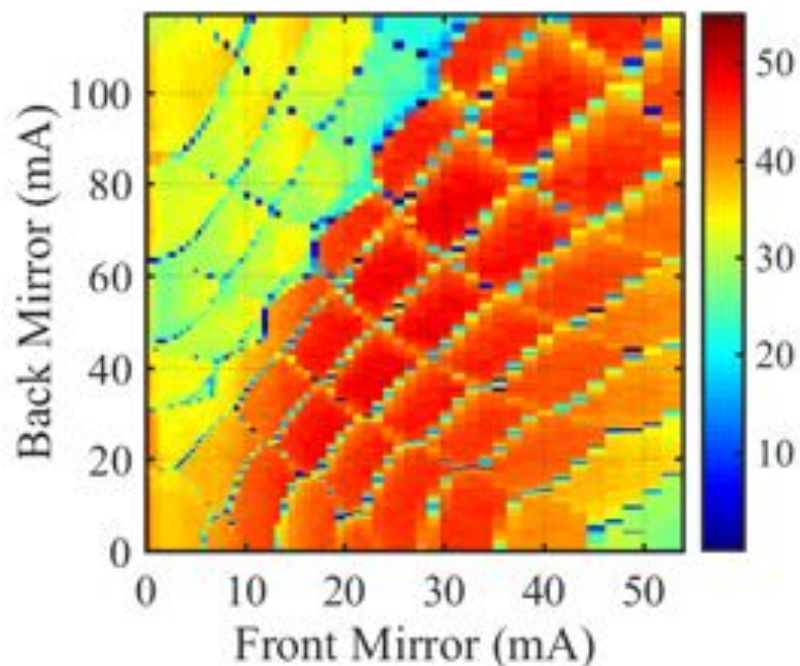
3.2 PIC characterization

Emission Wavelength



44-nm tuning range

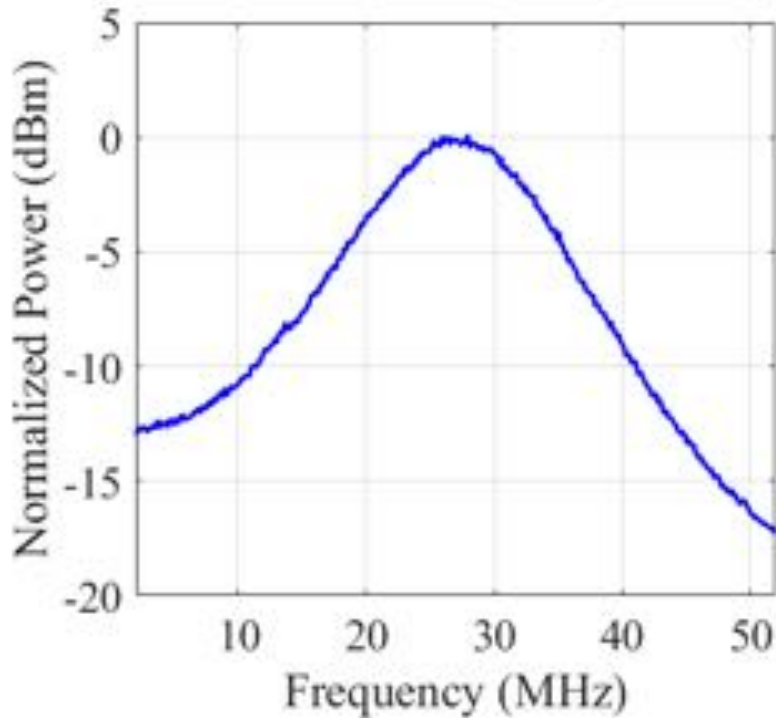
Side Mode Suppression Ratio



> 45 dB SMSR

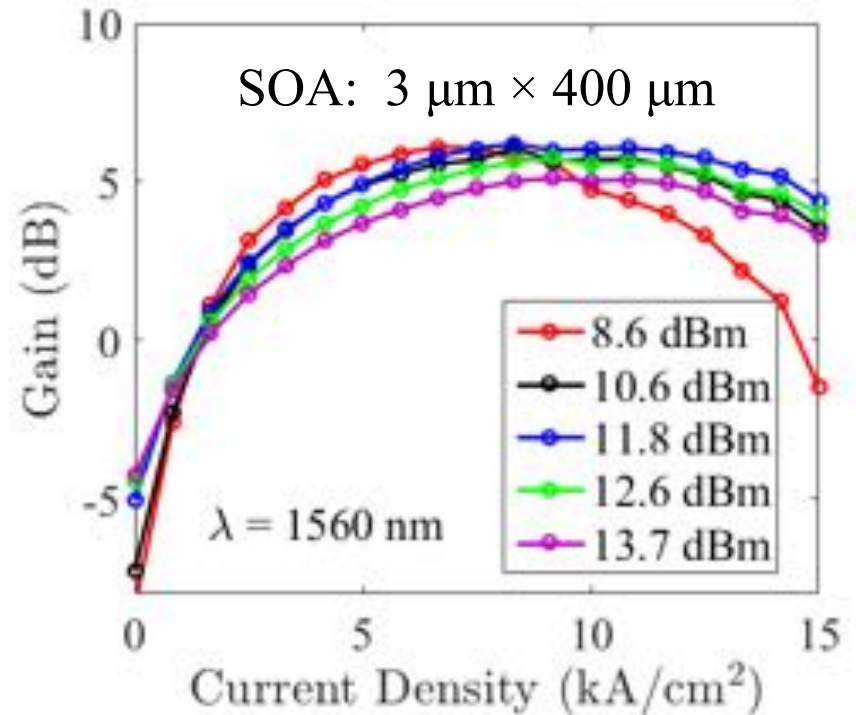
3.2 PIC characterization

Laser linewidth (heterodyne)



6.4-MHz 3-dB linewidth

SOA gain characteristic



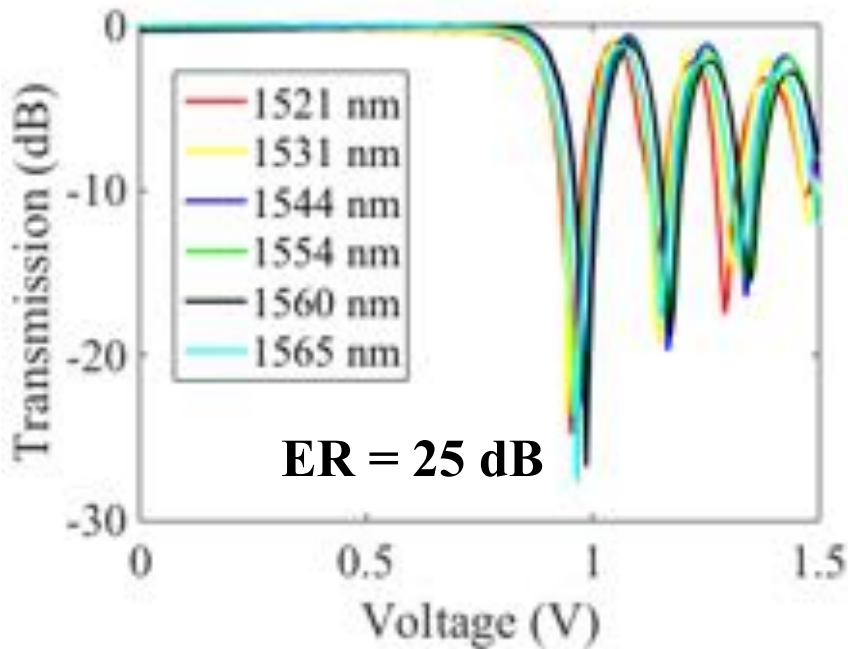
6 dB saturation gain

3.2 PIC characterization

DC Transfer Function of MZM

Forward bias

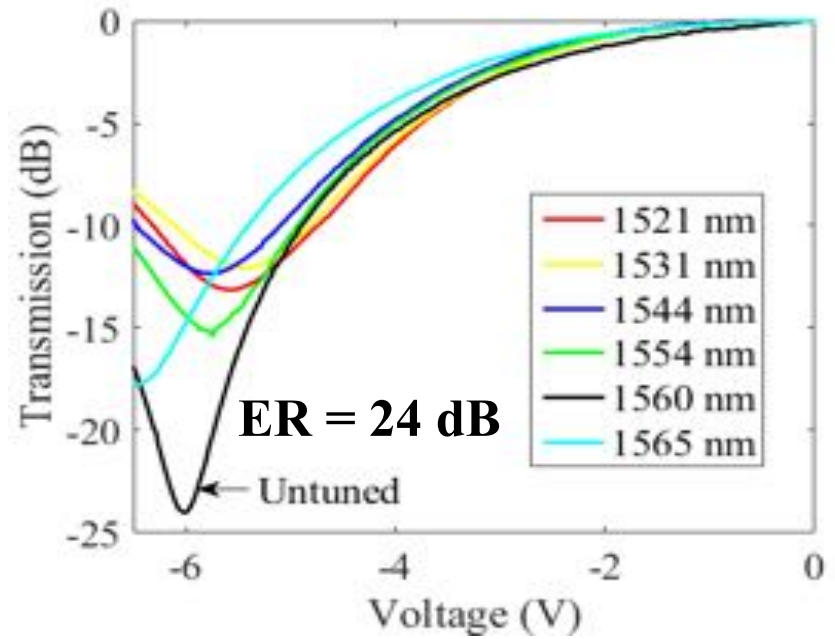
Low data-rate applications (1 Gbps)



$V\pi = 0.2 \text{ V}$

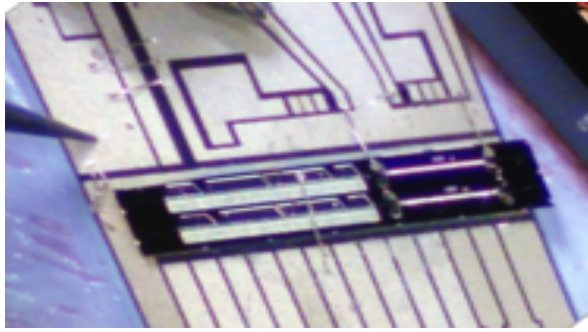
Reverse bias

Higher data rate applications



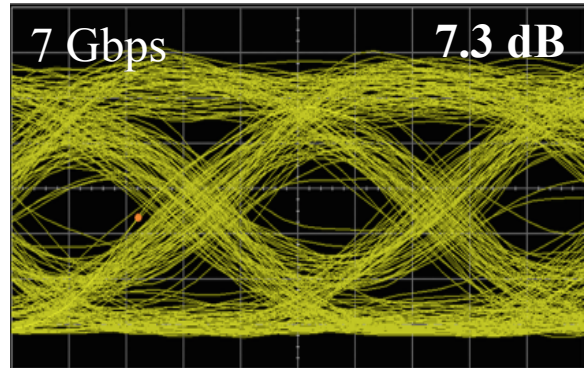
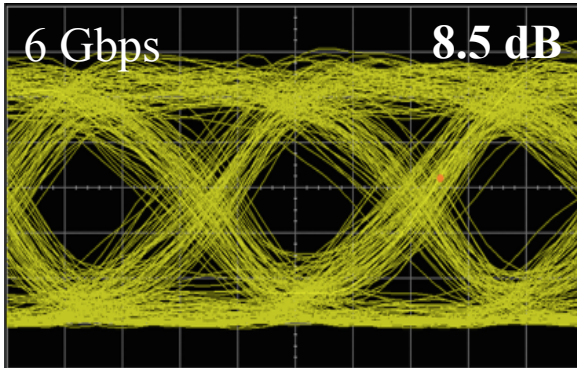
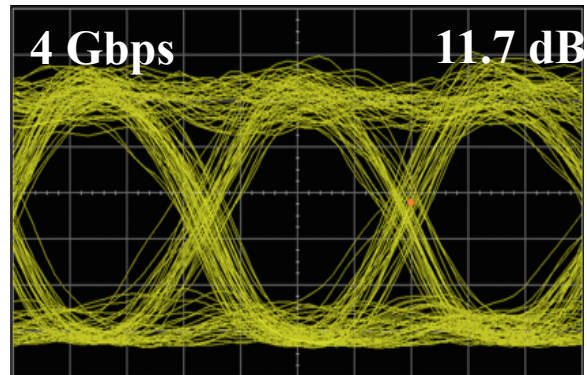
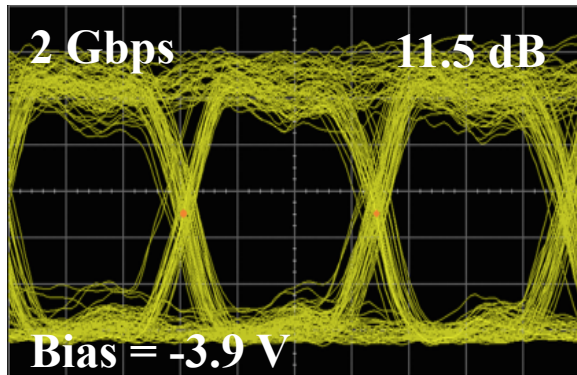
$V\pi = 6 \text{ V}$

3.2 PIC characterization

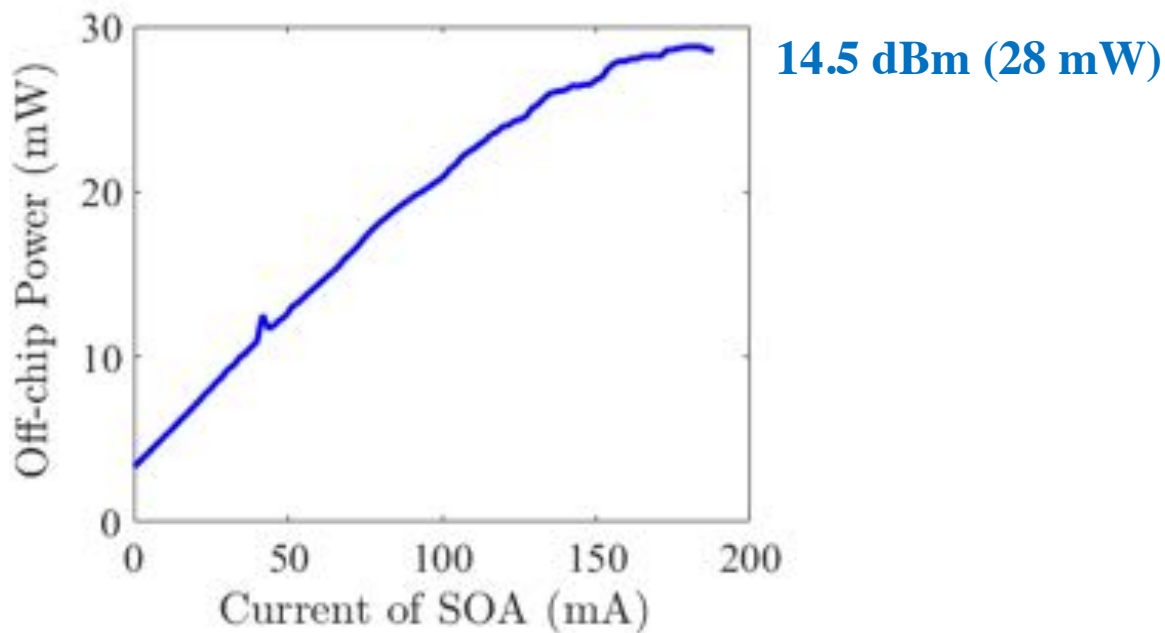
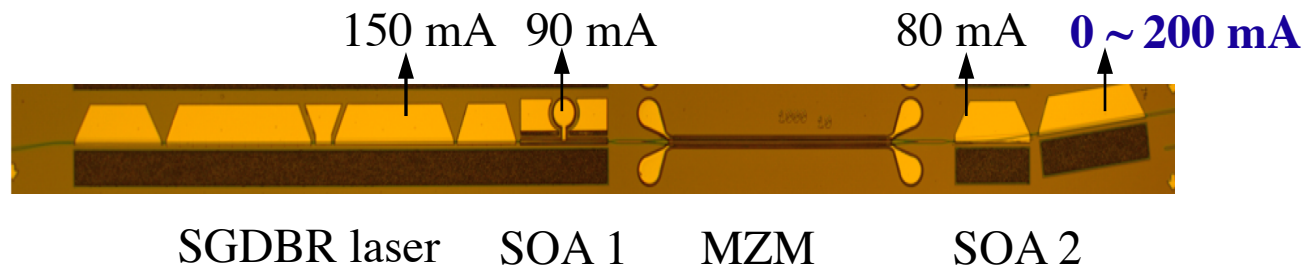


Devices mounted on ceramic carrier

NRZ OOK Modulation



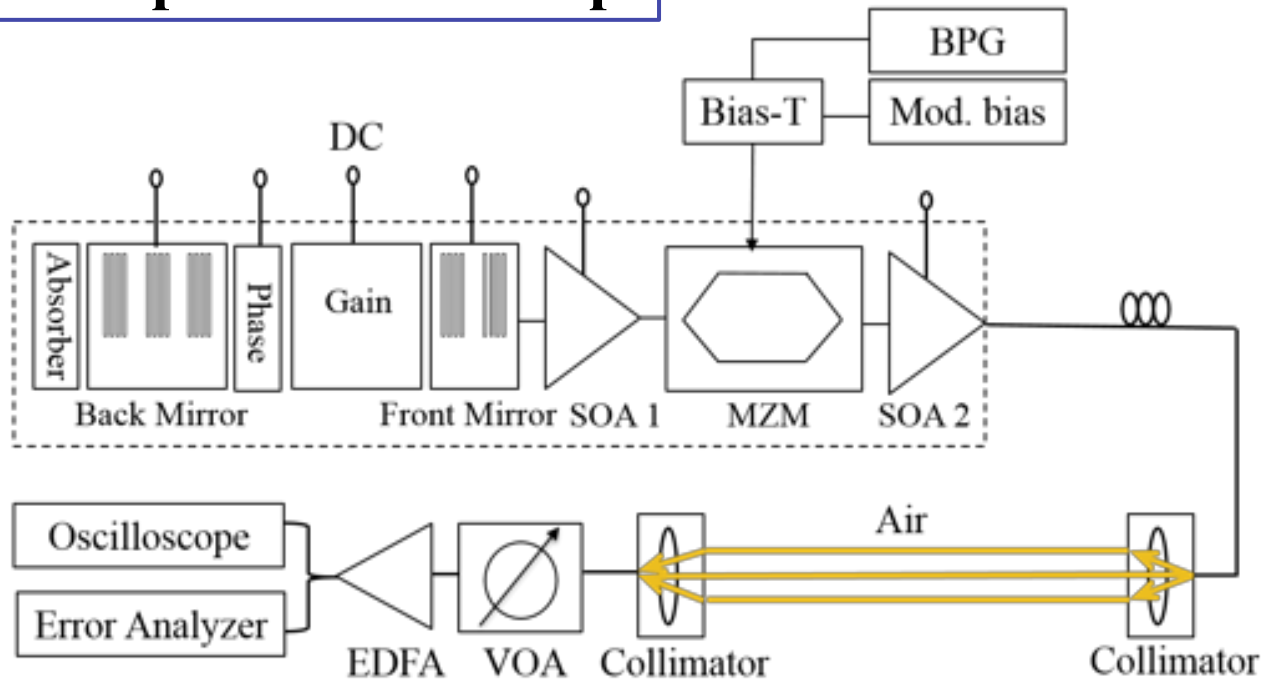
3.2 PIC characterization



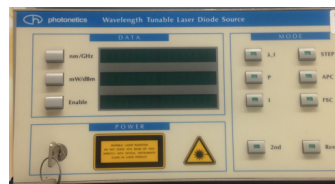
Off-chip Optical Power

3.3 Free space link

Free Space Optical Link Setup



Collimator



External Cavity Laser



10 GHz Commercial MZM

Reference

3.3 Free space link

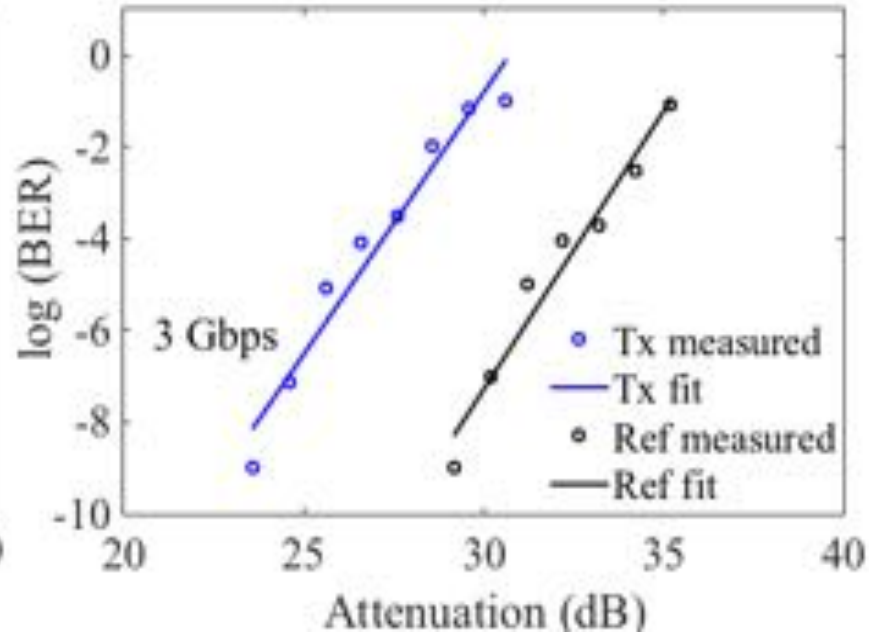
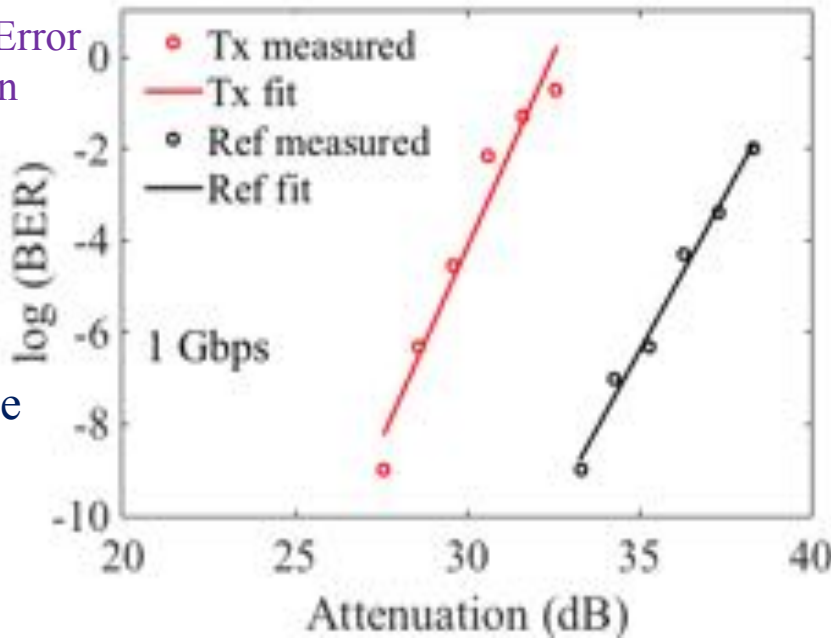
Bit-Error-Rate Measurement

Forward Error Correction

2×10^{-3}

Error free

1×10^{-9}



Error free: 300 m (28 dB)

180 m (24 dB)

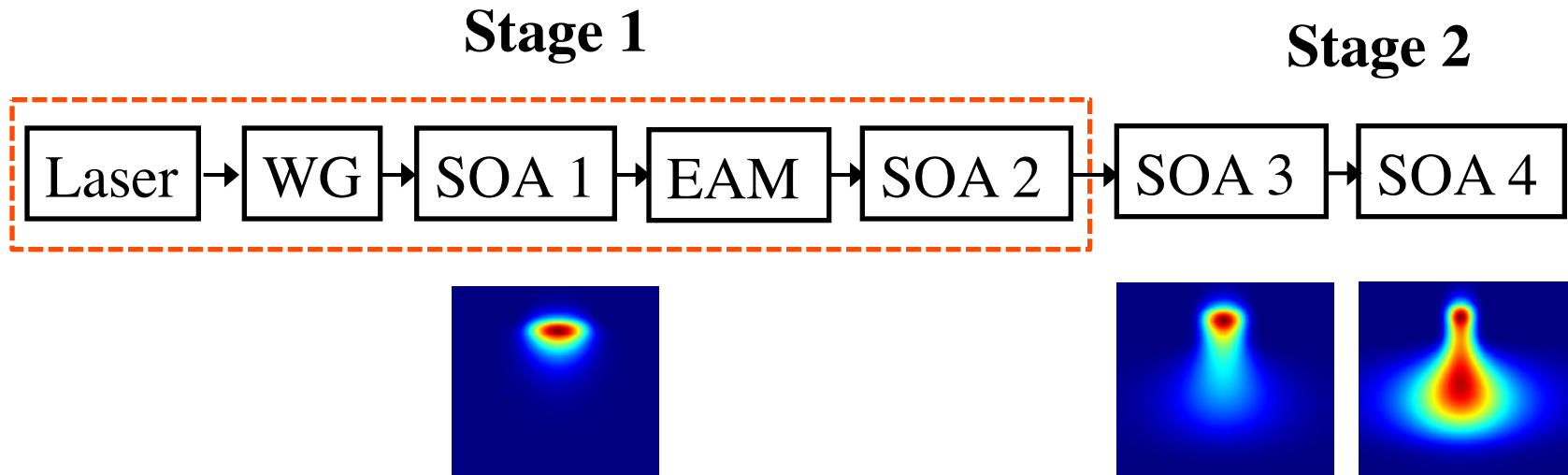
FEC: 400 m (30 dB)

300 m (28 dB)

Outline

- ❖ 1. Background
- ❖ 2. Epi design
- ❖ 3. OQW-based PIC transmitter
- ❖ **4. QWI-based PIC transmitter**
 - 4.1 Fabrication process
 - 4.2 PIC transmitter
 - 4.3 High-power SOAs
- ❖ 5. Future work

4.1 Fabrication process



Stage 1: high-confinement WG

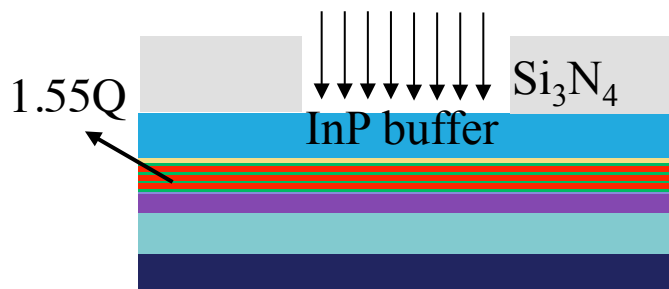
SOA 3: transition tapers

SOA 4: low-confinement SOA

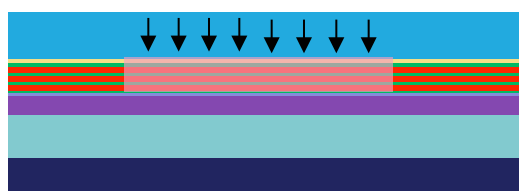
4.1 Fabrication process

Quantum Well Intermixing

Low-energy ion implant



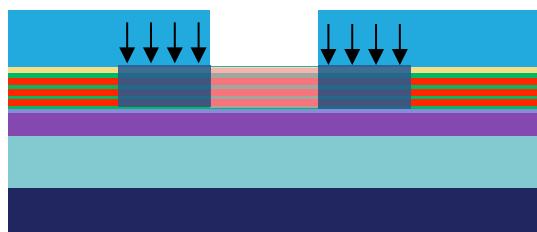
Rapid thermal anneal



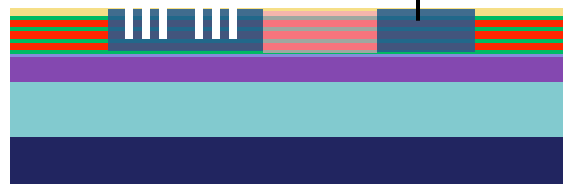
1.49Q



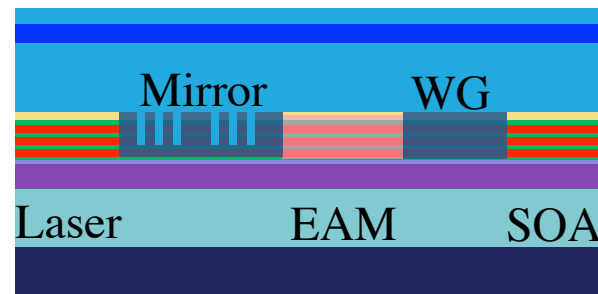
Anneal



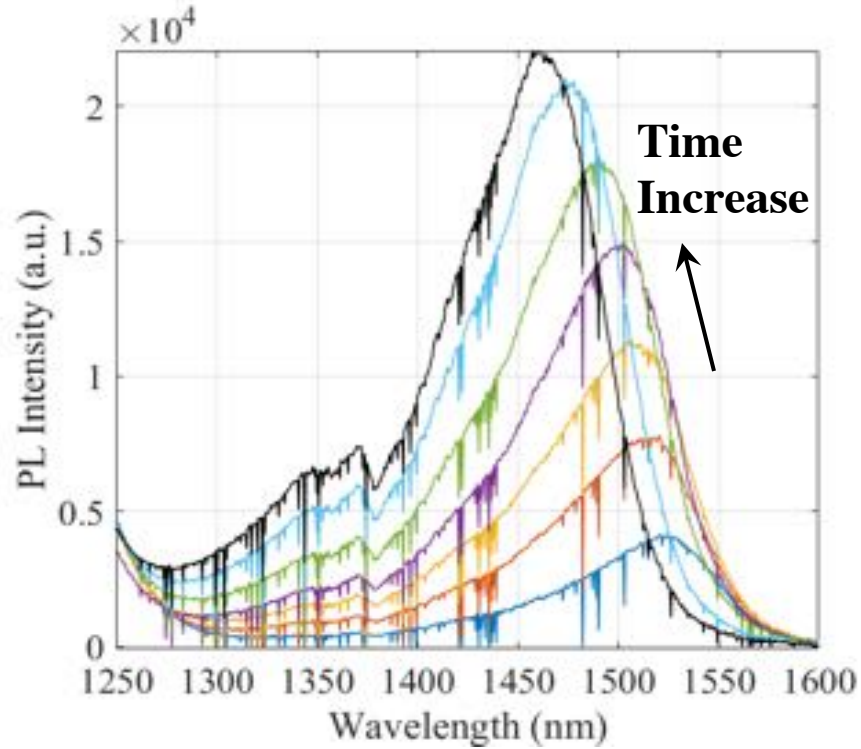
Grating etch 1.45 Q



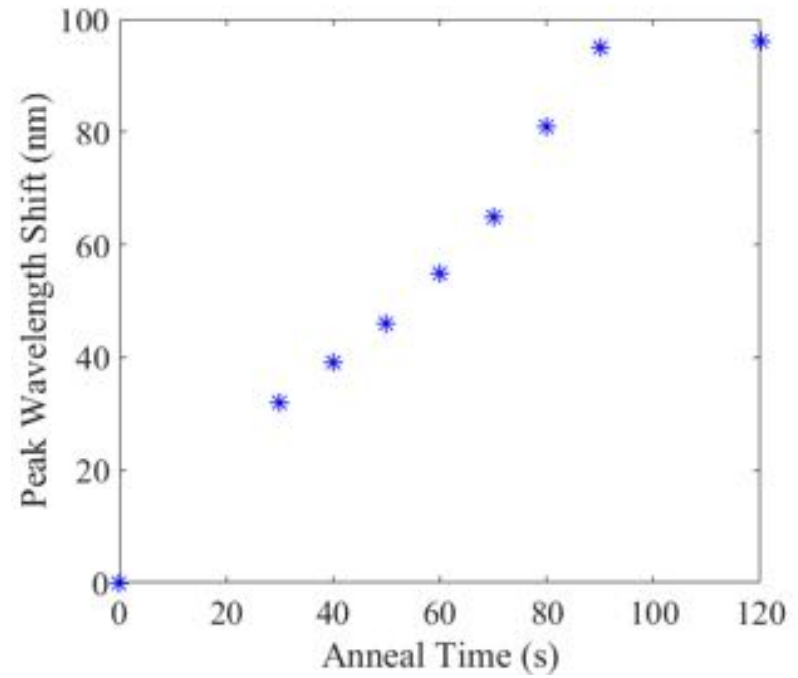
Regrowth



4.1 Fabrication process



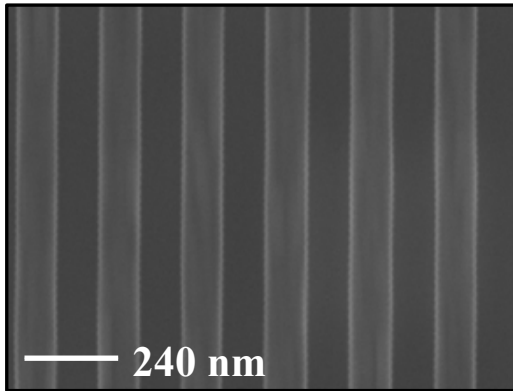
PL vs anneal time



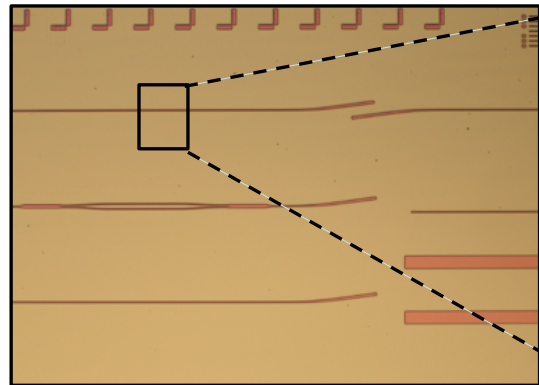
Bandgap shift

4.1 Fabrication process

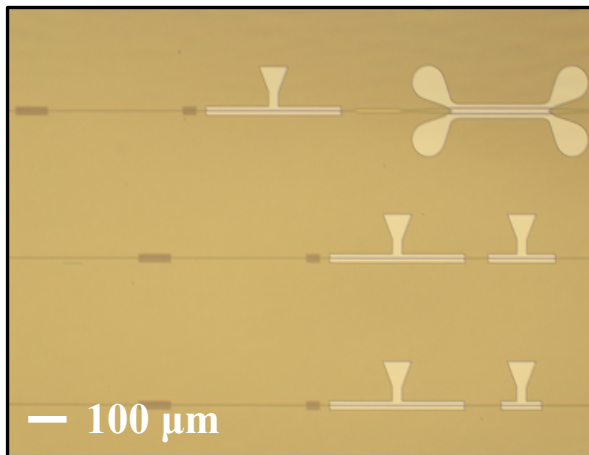
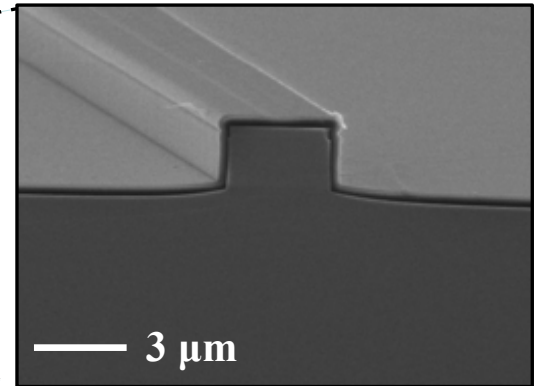
Grating by E-Beam litho



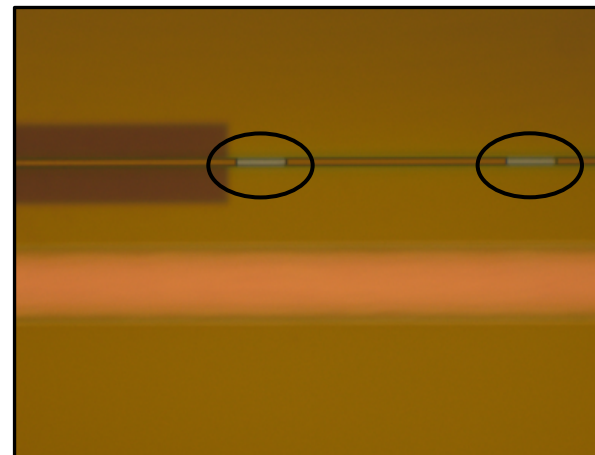
Ridge definition



Cross-section of ridge WG

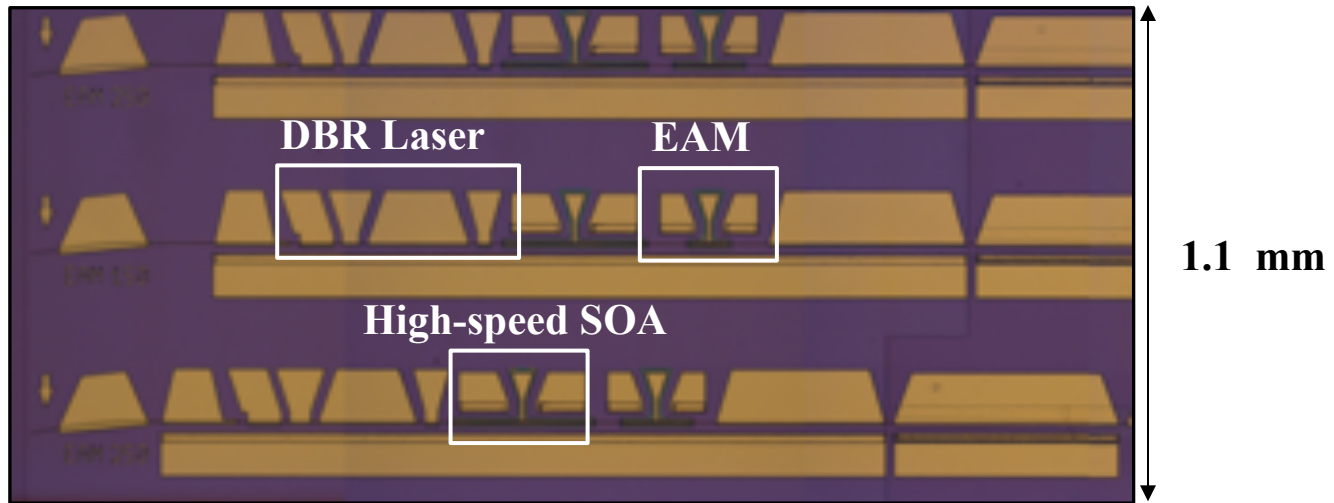
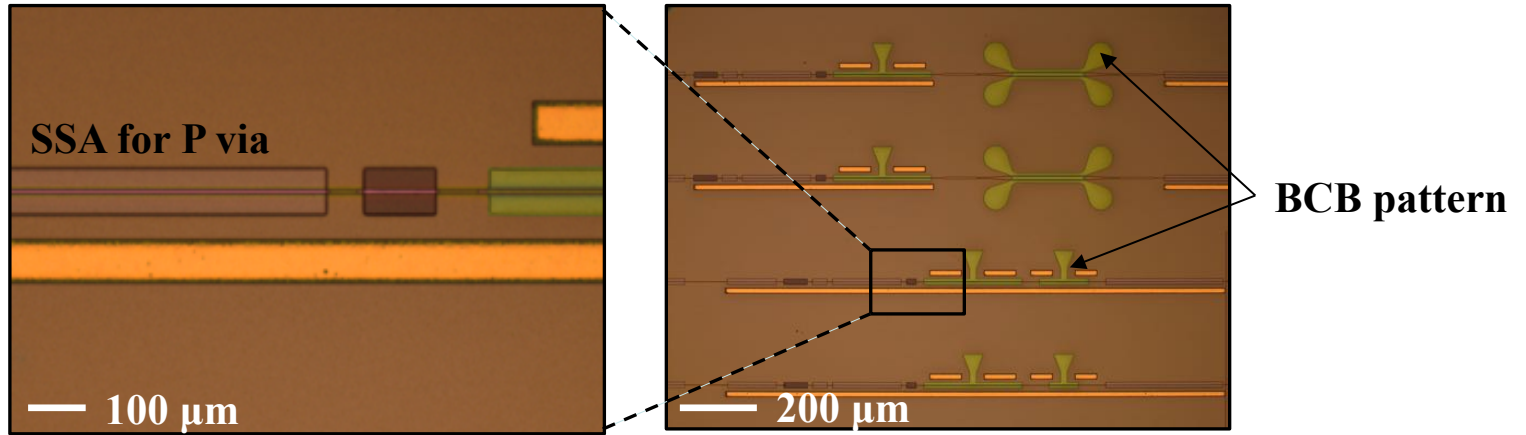


Passivation etch



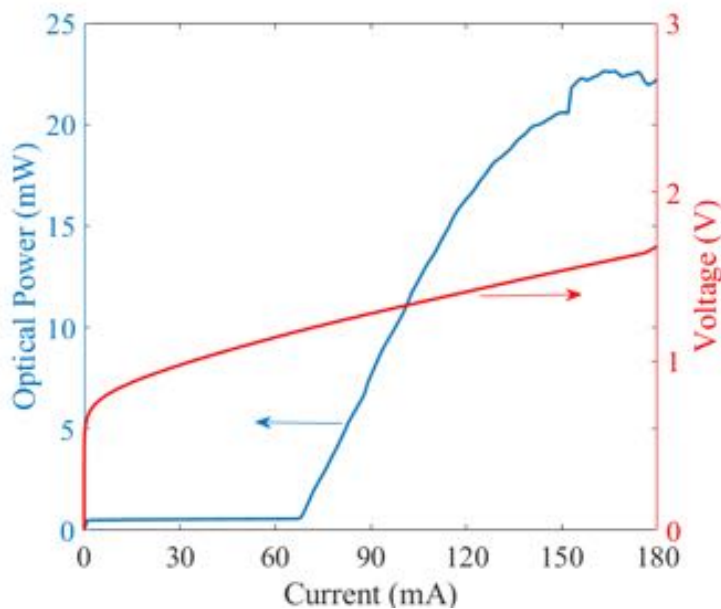
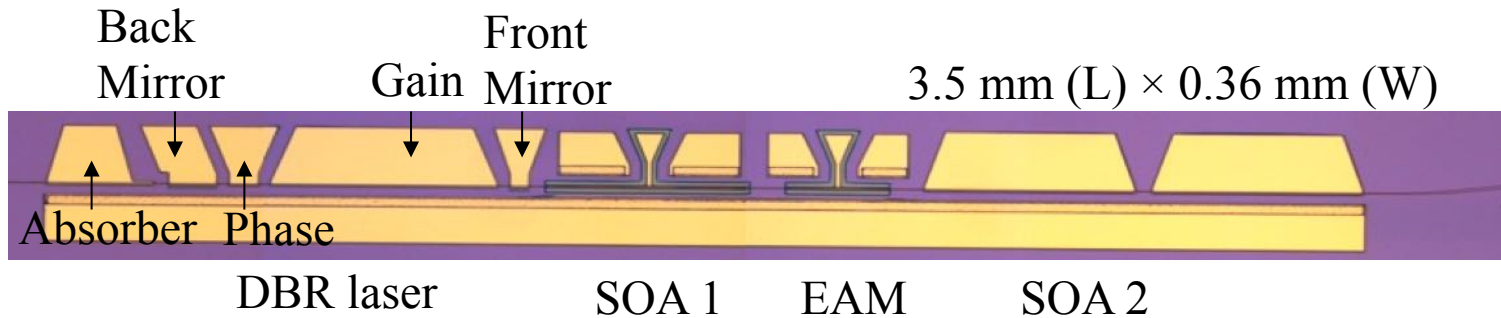
Isolation

4.1 Fabrication process

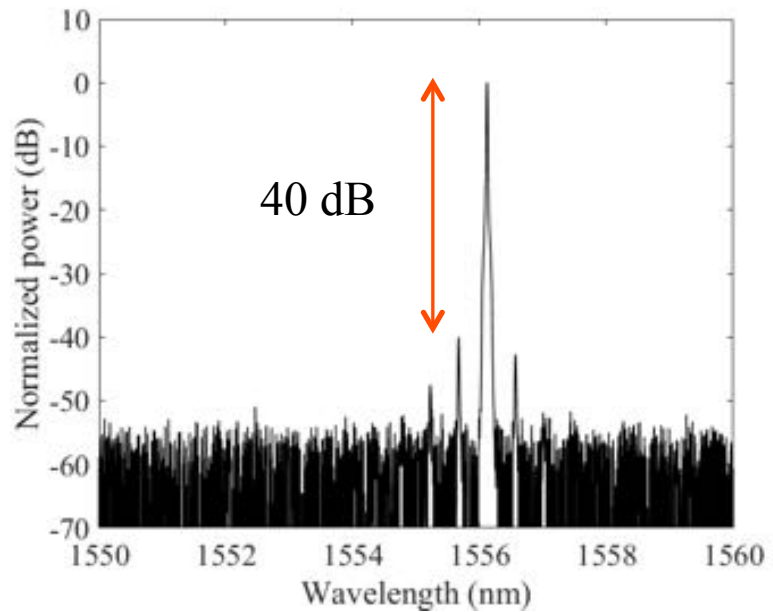


Fabricated PICs

4.2 PIC transmitter



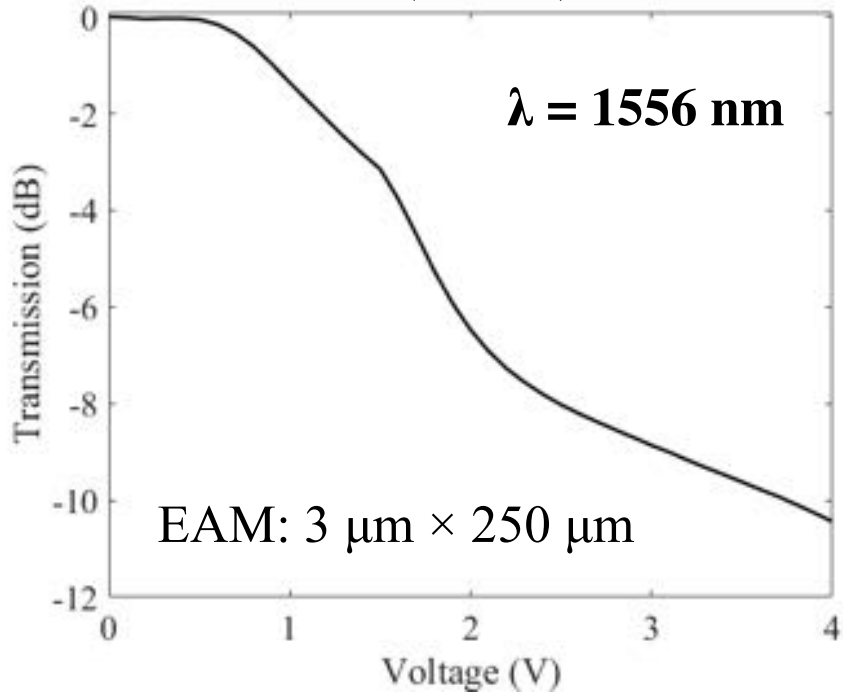
CW LIV characteristic



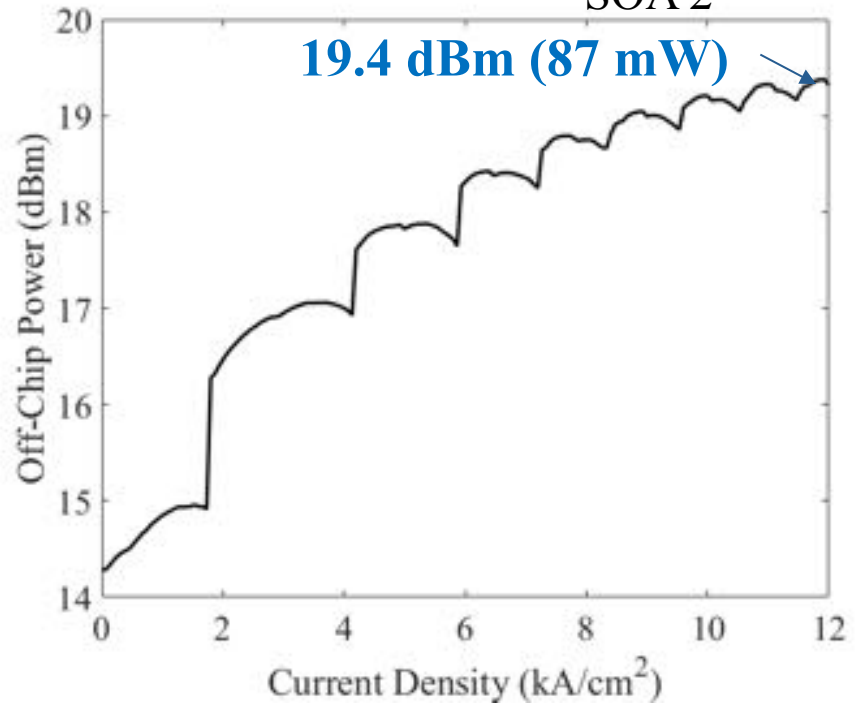
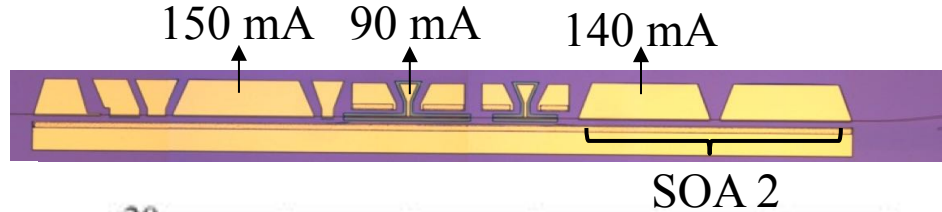
Laser spectrum (Resolution: 0.02 nm)

4.2 PIC transmitter

Electro-absorption modulator (EAM)



DC Transfer function

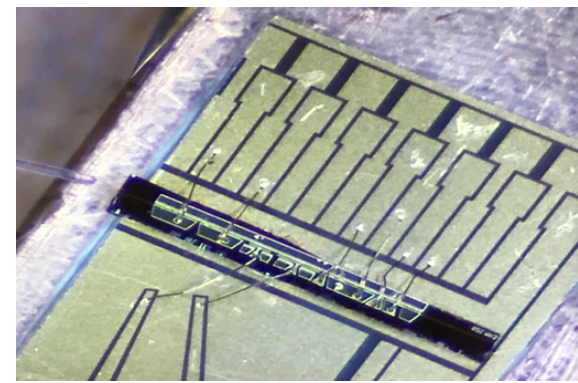
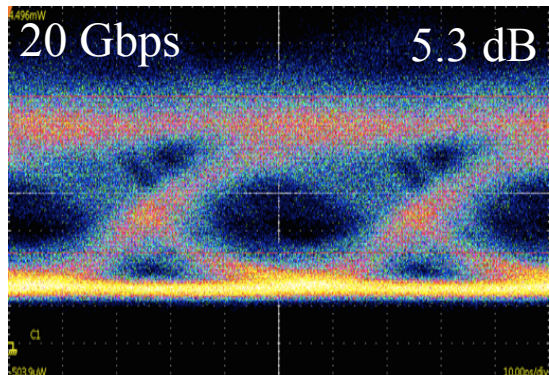
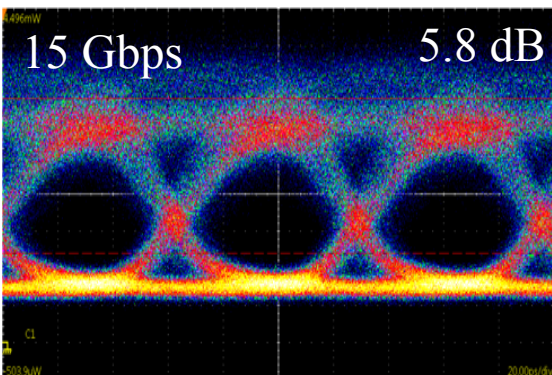
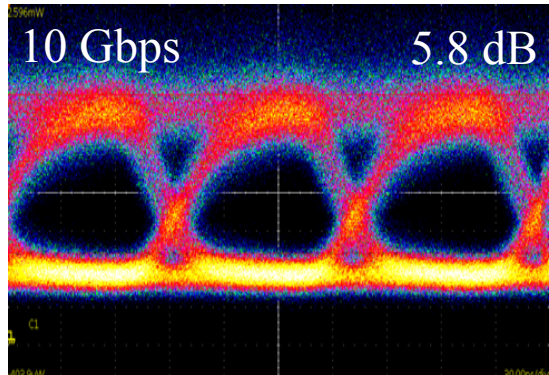
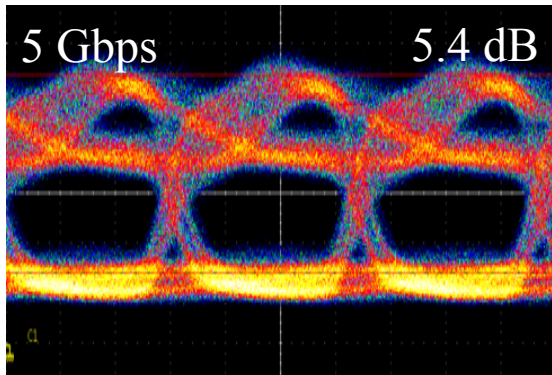


Off-chip optical power

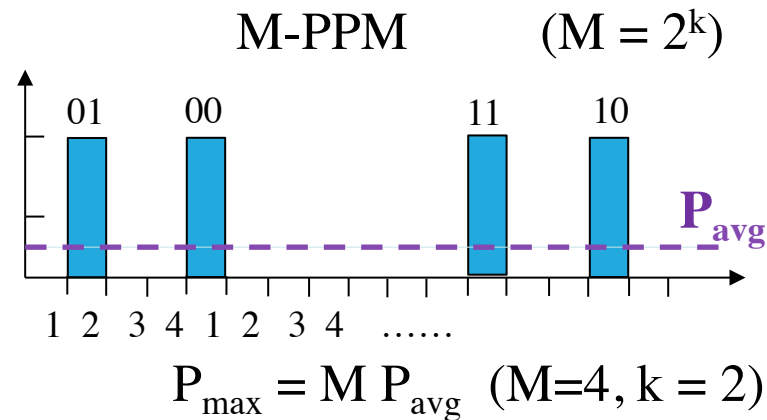
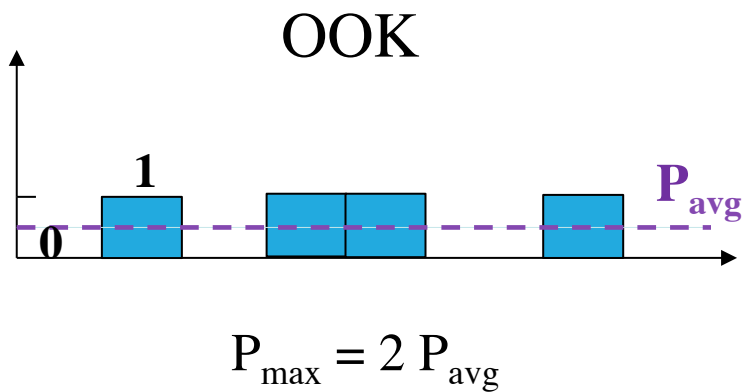
5 dB > OQW Tx

4.2 PIC transmitter

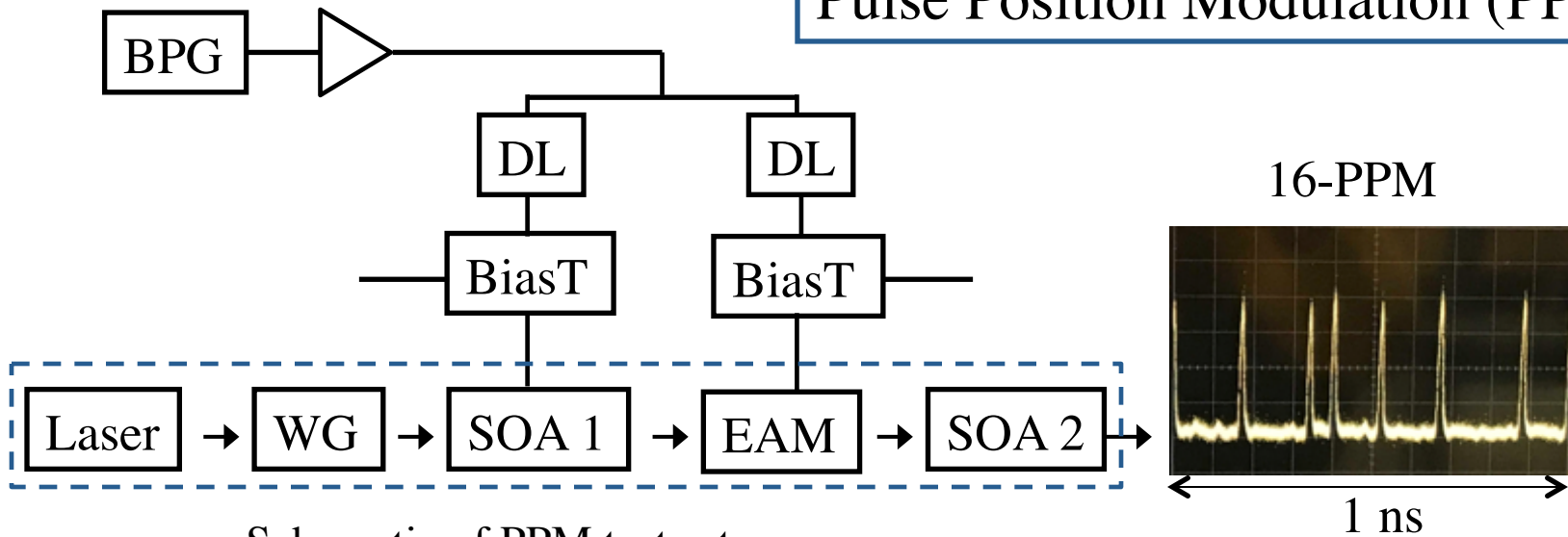
NRZ OOK Modulation



4.2 PIC transmitter



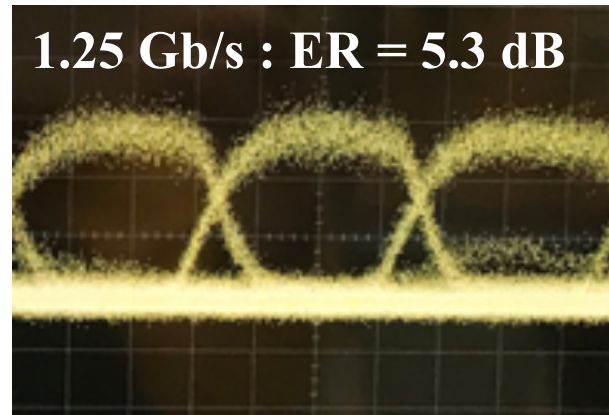
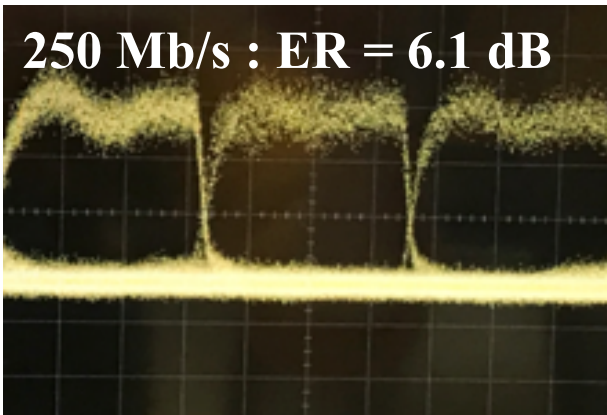
Pulse Position Modulation (PPM)



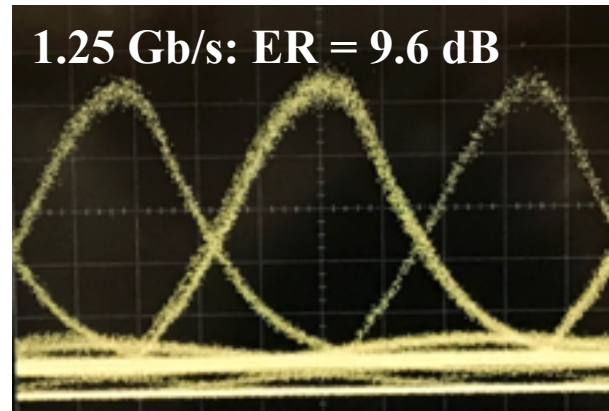
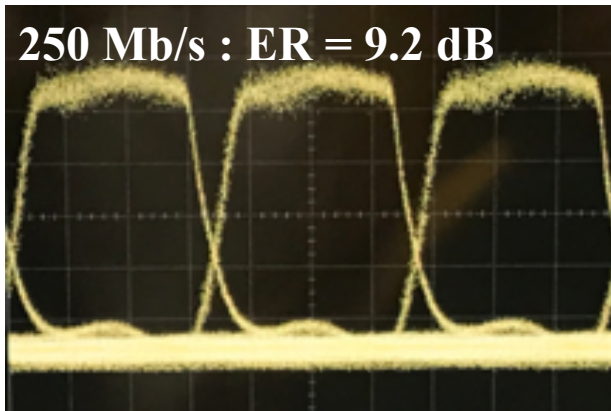
4.2 PIC transmitter

16-PPM

EAM modulated

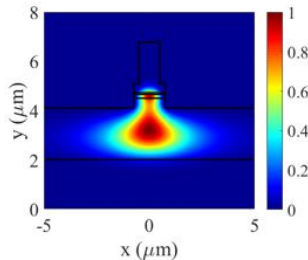
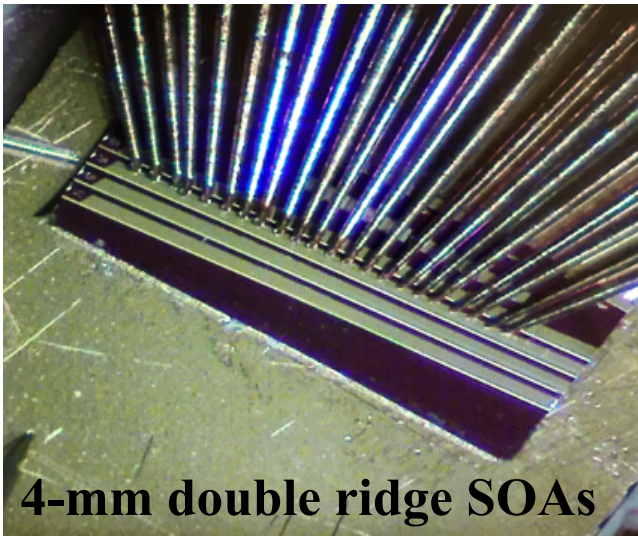
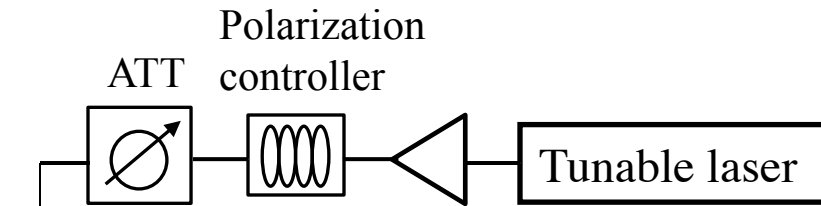


Both EAM and SOA1 modulated

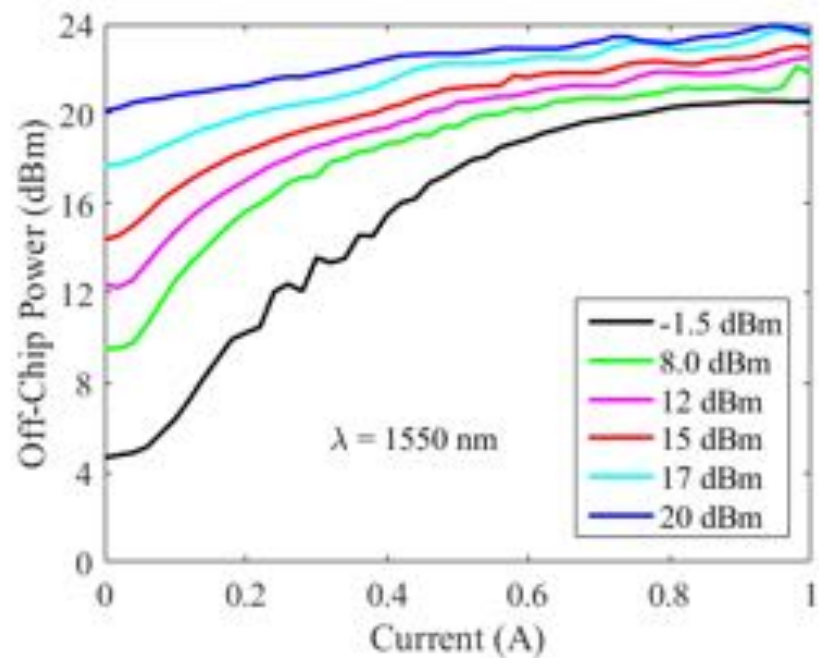


Low data rate applications

4.3 High power SOA



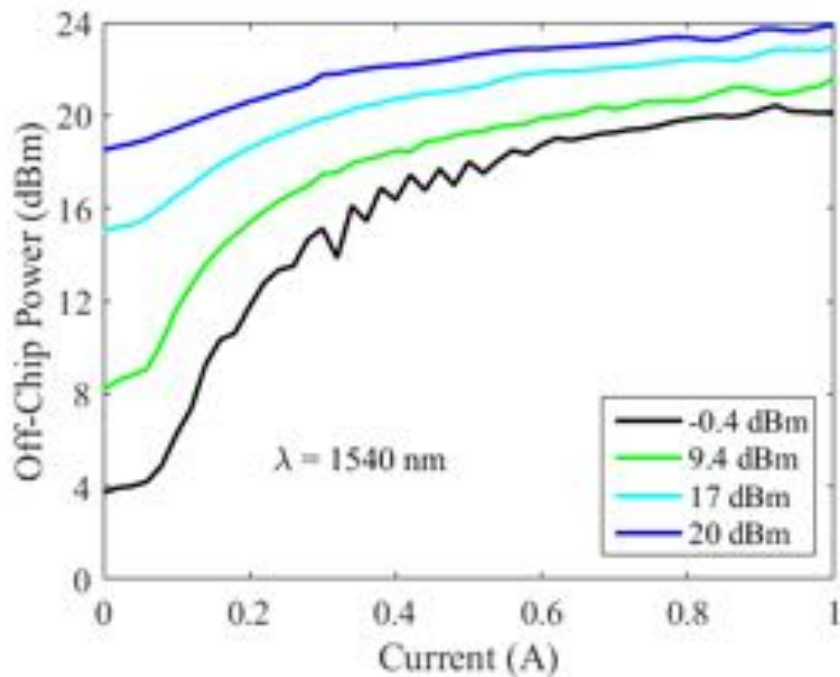
Off-chip optical power



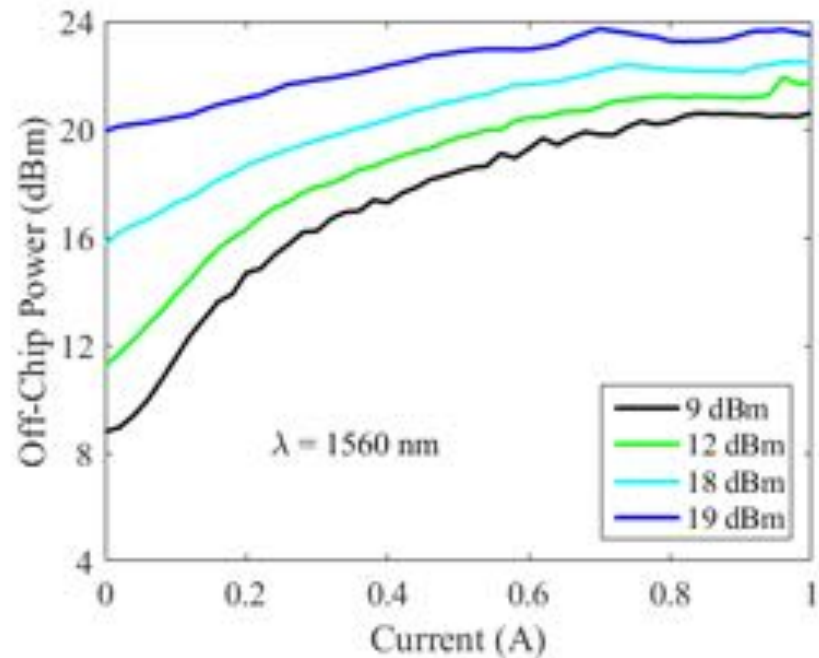
**Max optical power:
24 dBm (250 mW)**

4.3 High power SOA

Broadband Operation



Max optical power: 23.9 dBm



Max optical power: 23.7 dBm

4.4 High-power SOA

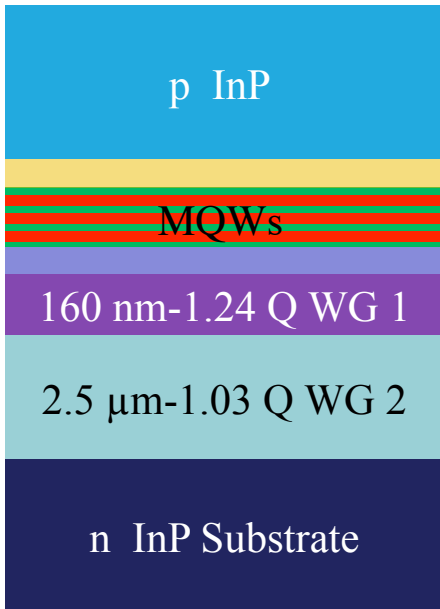
| Tx | Laser-MO | SOA | Data Rate | Link Length* |
|--------------|-----------------|------------|------------------|---------------------|
| OQW | 10 mW | 28 mW | 7 Gbps | ~ 300 m |
| QWI- Stage 1 | 10 mW | 87 mW | 20 Gbps | ~ 500 m |
| QWI- Stage 2 | 10 mW | 250 mW | 20 Gbps | ~ 900 m |

* Link length without HPA.

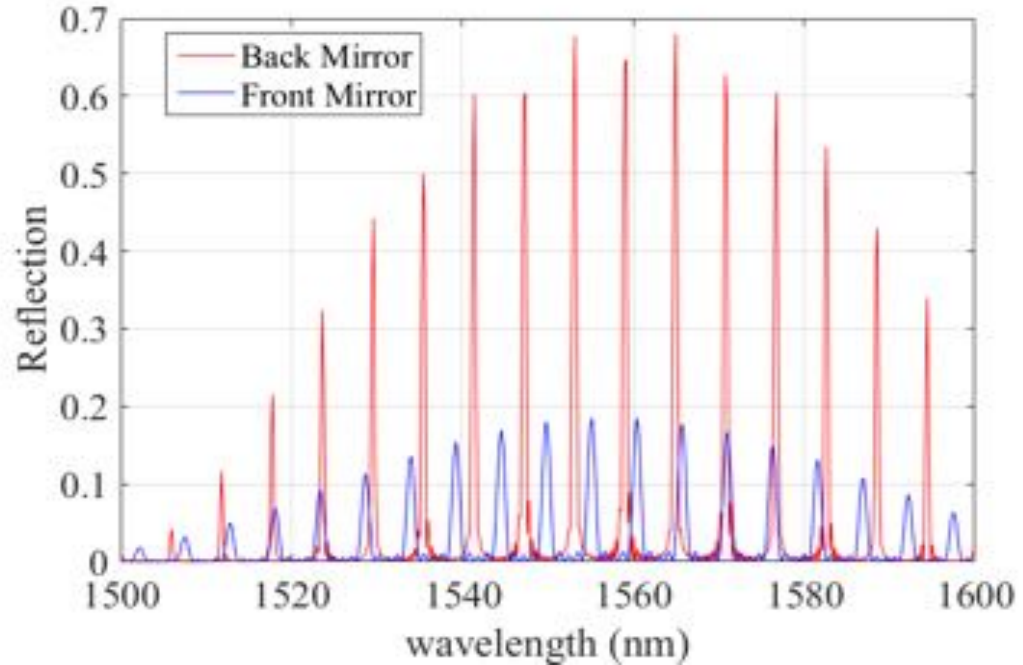
Outline

- ❖ 1. Background
- ❖ 2. Epi design
- ❖ 3. OQW-based PIC transmitter
- ❖ 4. QWI-based PIC transmitter
- ❖ **5. Future work**

5. Future work



SGDBR laser



Front mirror: $W = 4 \mu\text{m}$, $P = 68.5 \mu\text{m}$, $M = 5$
 Back mirror: $W = 6 \mu\text{m}$, $P = 61.5 \mu\text{m}$, $M = 12$

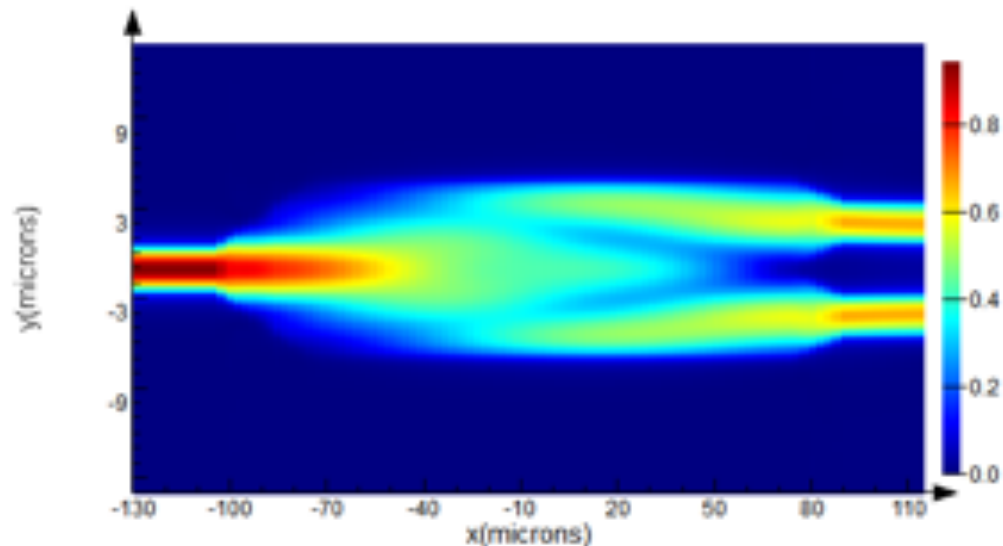
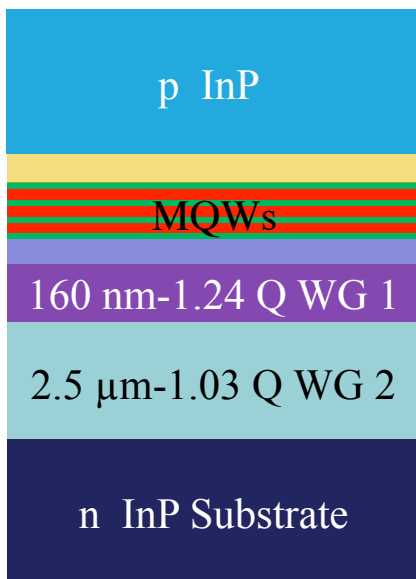
5 μm

15

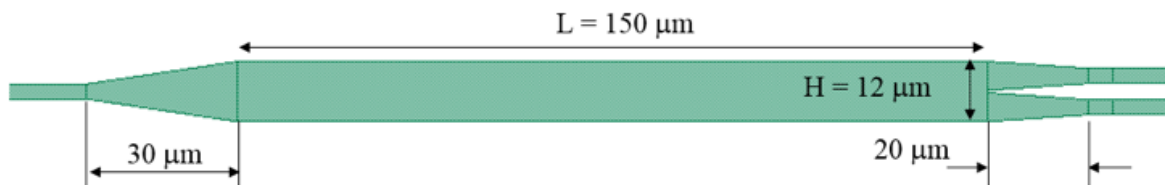
5. Future work



Mach-Zehnder Modulator

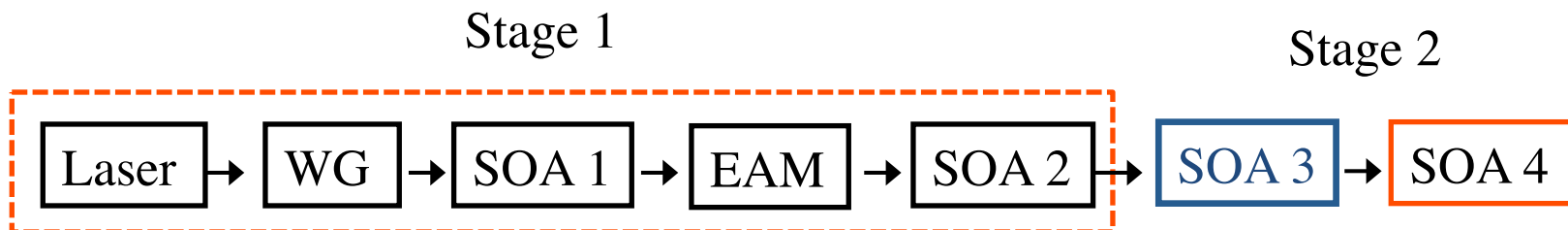


EME simulation of a 1×2 coupler

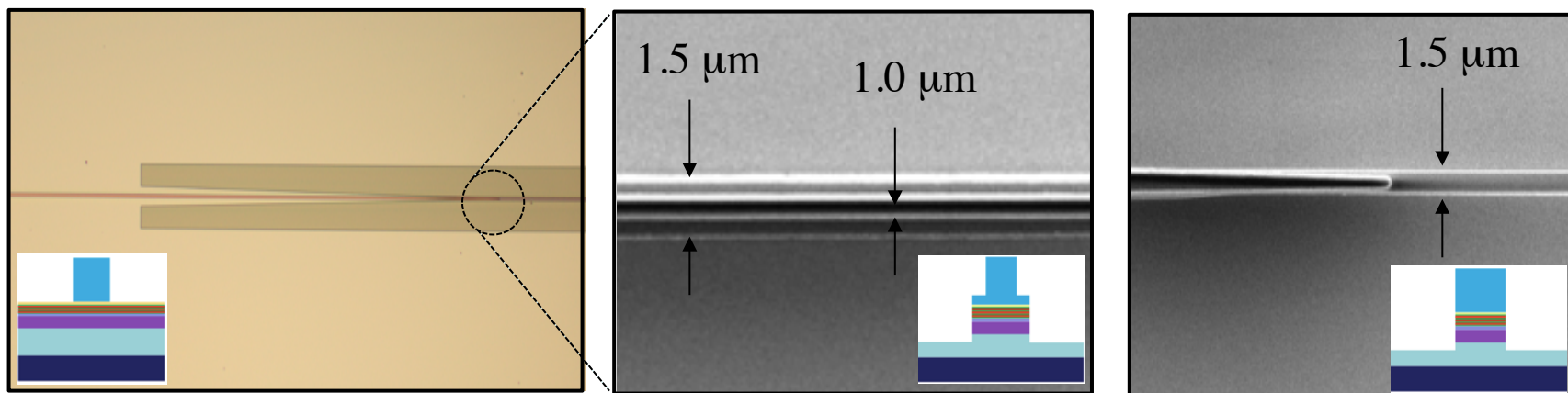


1×2 coupler

5. Future work



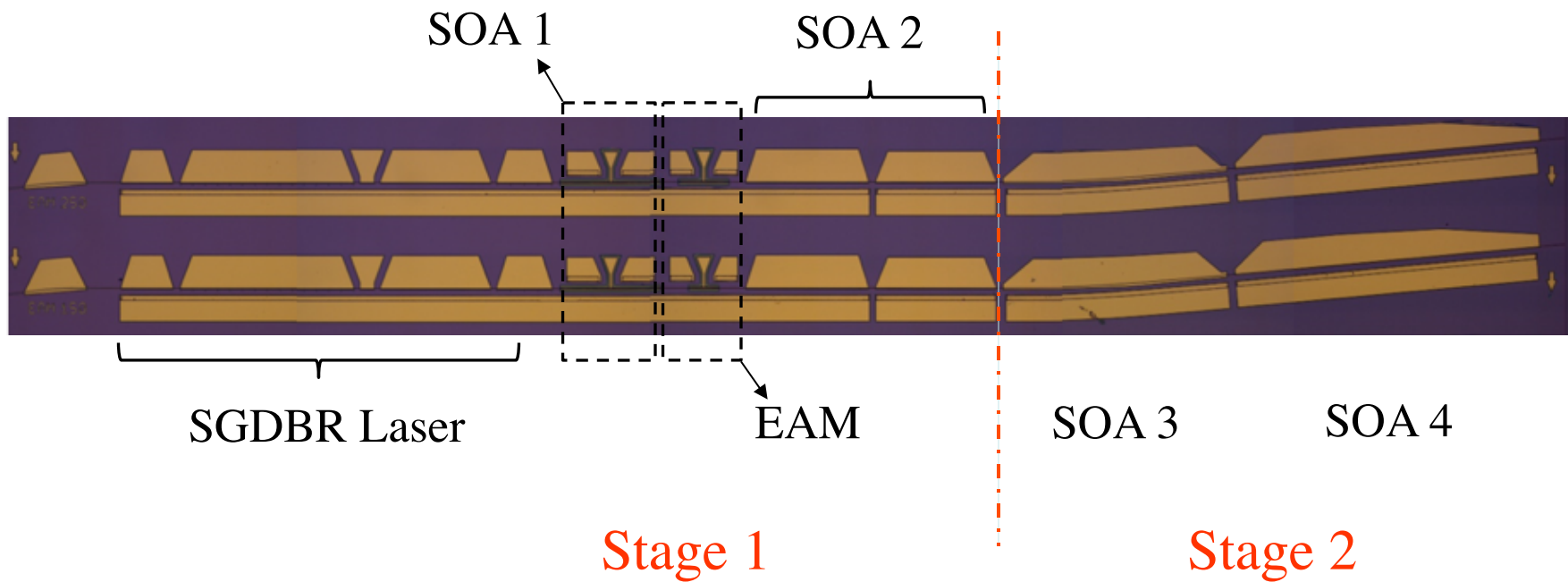
Transition section



Full integration of Stage 1 Tx with advance high-power SOAs

5. Future work

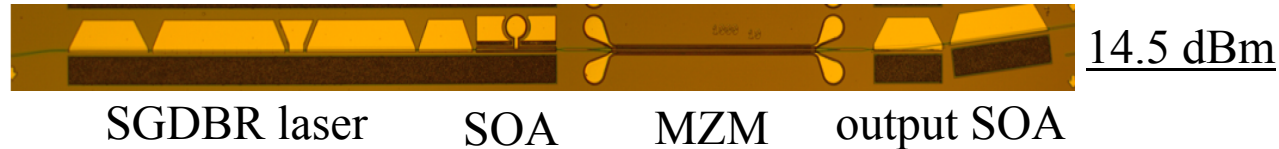
8 mm (L) × 0.36 mm (W)



PIC Tx integrated with advanced SOAs

Summary

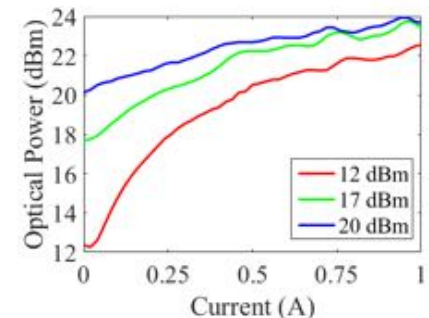
➤ Gen 1 OQW Tx



➤ Gen 2 QWI Tx



➤ Gen 2 low- Γ SOA



➤ Demonstrated a high-power PIC platform for low CSWaP free space transceivers for small satellite applications

- PIC transmitter with 20-Gbps modulator and high-power booster SOA;
- Advanced SOA up to 24 dBm output power.

Acknowledgement

Thanks